

HTS Materials and Devices for Digital Applications

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- **Motivation for HTS Josephson-based electronics**
- **Junction status**
 - **Junction configurations**
 - **Progress in meeting desired junction parameters**
 - **What we think we understand**
- **Multilayer process development**
- **Some example HTS circuits**
- **Specific applications of interest to Northrop Grumman**
 - **A/D converters**
 - **D/A converters**
- **Issues & Summary**

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The logo consists of the text "NORTHROP GRUMMAN" in a blue, italicized, sans-serif font. Below the text is a blue, curved line that starts under the "N" and ends under the "M", arching upwards.

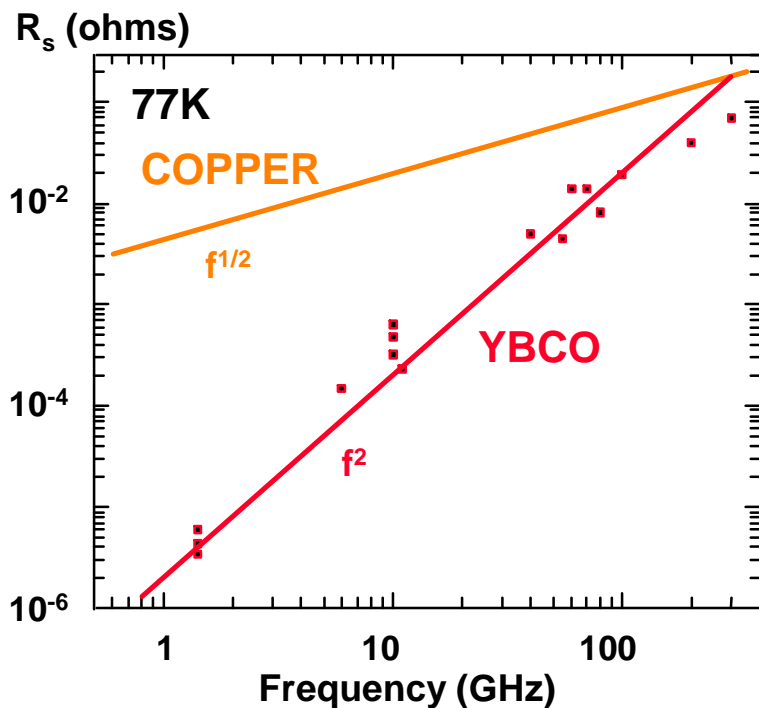
HTS Materials and Devices for Digital Applications: Bibliography

These papers are written by Northrop Grumman authors whose material is mainly used in this presentation. Other relevant papers can be found in the same sources, particularly in the proceedings of the 1998 Applied Superconductivity Conference published in Vol. 9 No. 2 of the *IEEE Trans. on Applied Superconductivity* (1999).

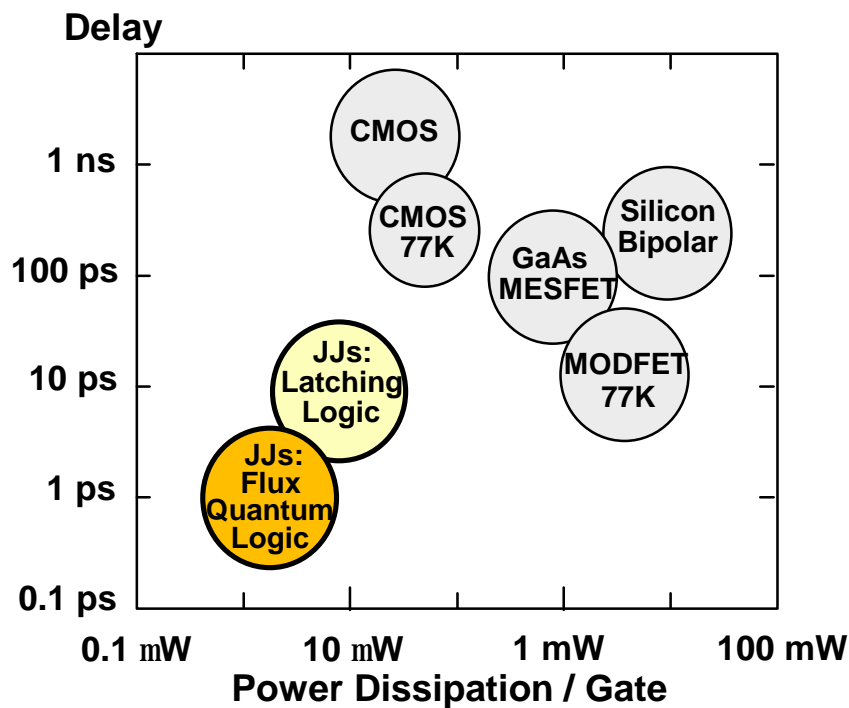
- B. D. Hunt, M. G. Forrester, and J. Talvacchio, "HTS Josephson Junction Development," in *Encyclopedia of Electrical and Electronics Engineering*, edited by J. G. Webster (John Wiley & Sons, New York, 1999).
- J. X. Przybysz, S. B. Kaplan, D. L. Miller, and S. V. Rylov, "Superconducting Analog to Digital Converters," in *Encyclopedia of Electrical and Electronics Engineering*, edited by J. G. Webster (John Wiley & Sons, New York, 1999).
- B. D. Hunt, M. G. Forrester, J. Talvacchio, and R. M. Young, "High-Resistance HTS Edge Junctions for Digital Circuits," *IEEE Trans. on Applied Superconductivity* 9(2), 3362 (1999).
- J. Talvacchio, M. G. Forrester, B. D. Hunt, J. D. McCambridge, R. M. Young, and X. F. Zhang, and D. J. Miller, "Materials Basis for a Six-Level Epitaxial HTS Digital Circuit Process," *IEEE Trans. on Applied Superconductivity* 7(2), 2051 (1997).
- M. G. Forrester, B. D. Hunt, D. L. Miller, J. Talvacchio, and R. M. Young, "Analog Demonstration of an HTS Sigma-Delta Modulator with 27 GHz Sampling," *Supercond. Sci. Technol.* 12(11) 698-700 (1999).

Orders of Magnitude Performance Advantage From Superconductivity and Cryogenics

1. Low Surface Resistance:
Improved Performance
of Microwave Devices



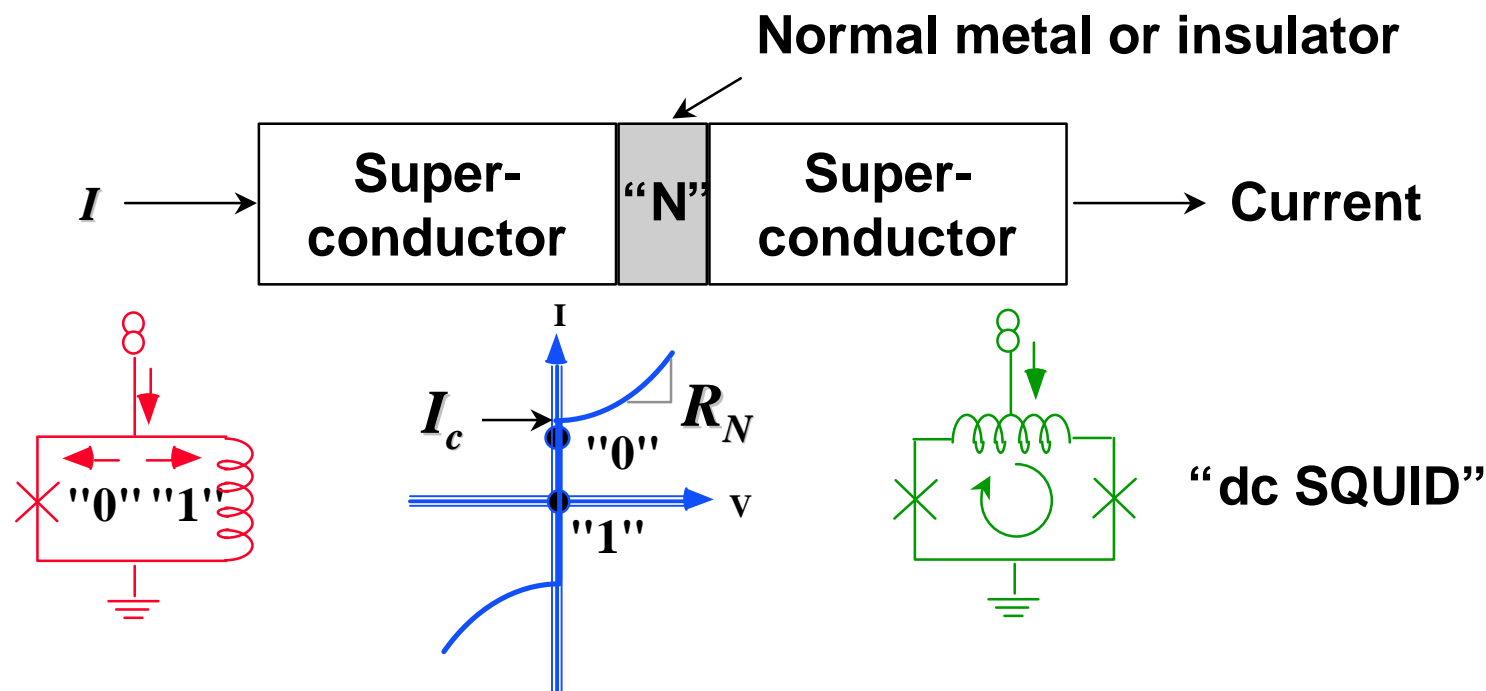
2. Reduced Power
Dissipation and Delay:
High-Speed Logic



3. Unique Quantum Accuracy:
Voltage Standard, DAC, ADC

4. Low Noise from
Cryogenic Operation

Josephson Junctions are the Building Blocks of Superconducting Digital Circuits



Picosecond transition between states

$\mathcal{P} \sim 100$ GHz clock speed attainable

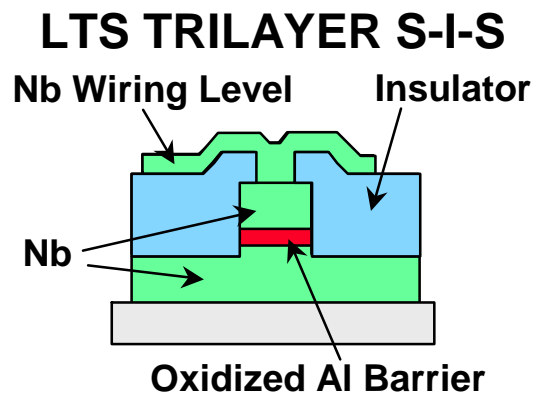
Digital "1" & "0" both zero voltage

\mathcal{P} low power dissipation (μ W/gate)

$$I = I_c \sin(f_L - f_R)$$

$$V = \frac{\hbar}{2e} \frac{df}{dt}$$

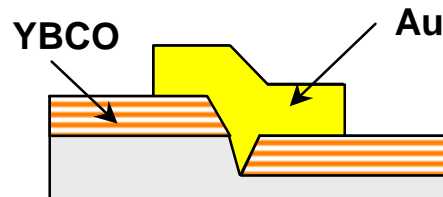
HTS vs. LTS Junction Configurations



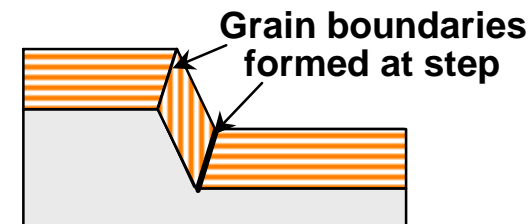
LTS Junctions:

- < 150°C processing
- randomly-oriented, polycrystalline films
- single-component films
- silicon substrates
- level of integration = 10,000s

STEP-EDGE S-N-S



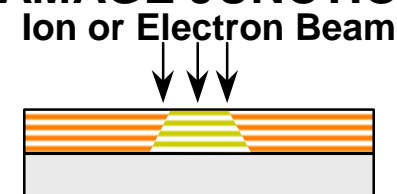
STEP-EDGE GRAIN BOUNDARY



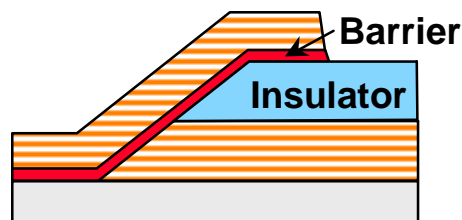
HTS Junctions:

- 750°C processing
- epitaxial, oriented films
- single-crystal oxide substrates
- level of integration = 10s

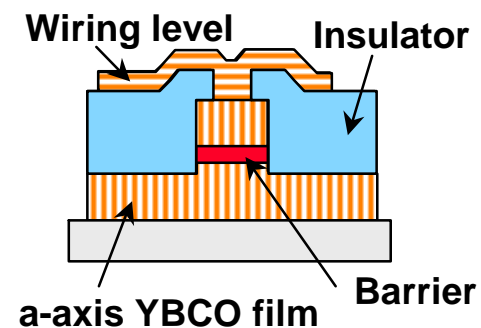
DAMAGE JUNCTIONS



EDGE S-N-S



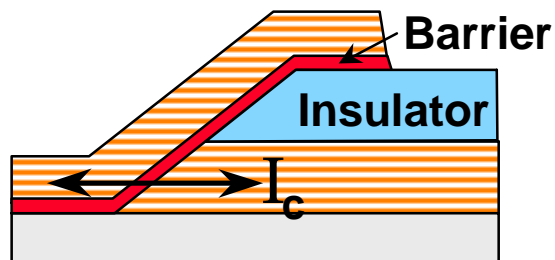
TRILAYER S-N-S



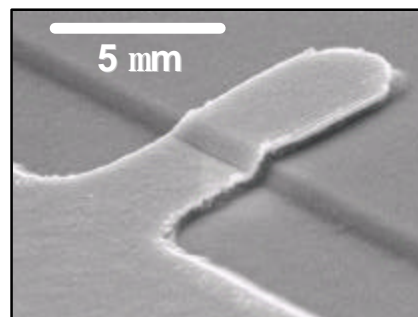
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Selection of an HTS Junction Configuration: Edge S-N-S Junctions

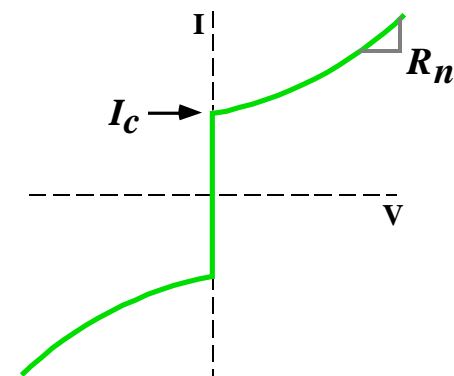
Schematic



SEM Micrograph

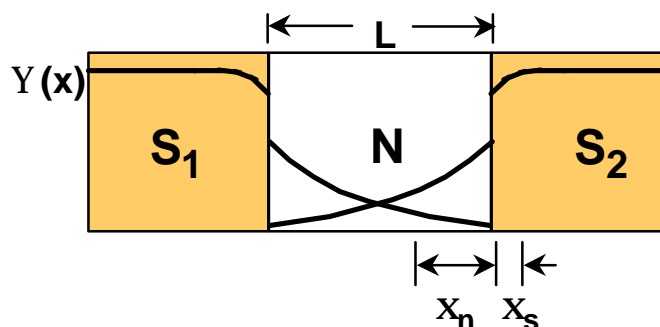


I-V Curve



Major Advantages of Edge SNS Junctions

- Contact to long- x_n and long- x_s directions of c-axis films
- 50 - 100 Å bridge lengths, L
(LTS junctions use ~ 8 Å thick tunnel barriers)
- Small device areas \bar{D} high R_n



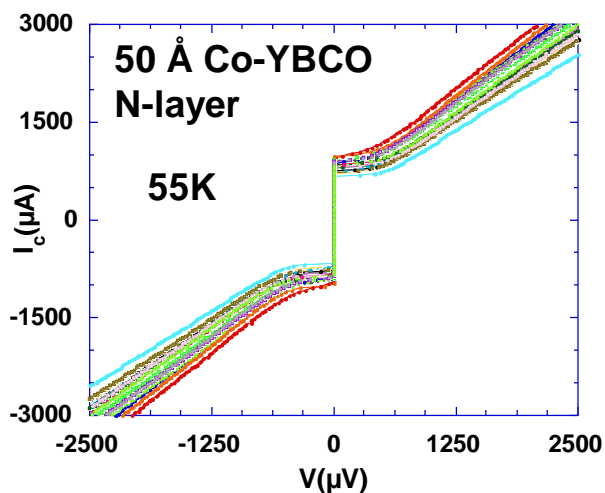
$$I_c \propto e^{-L/x_n}$$

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Progress in Meeting Required HTS Junction Parameters

- Single Flux Quantum designs require $LI_c \gg \Phi_0 = 2 \text{ pH-mA}$
- Thermal noise constraints require $I_c \gg 0.5 \text{ mA}$ ✓
 - SQUIDs must have low $L \gg 4 \text{ pH}$ ✓
 - Must use an integrated HTS ground plane ✓
 - Junctions must face in several directions ✓
- High R_n ($\sim 2 \text{ W}$) for digital output signals: $\max V = I_c R_n$ ✓
- Low R_n ($\sim 0.01 \text{ W}$) for ac voltage standards ✓
- Circuit margins limit I_c variation

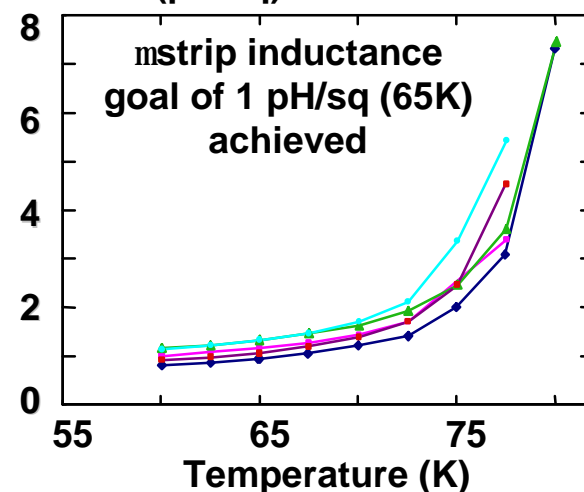
(we are working on it)



Average Junction Parameters:

- $I_c = 834 \text{ } \mu\text{A}$,
 $S_{Ic} = 10\%$
- $I_c R_n = 797 \text{ } \mu\text{V}$,
 $S_{Ic R_n} = 6\%$
- $R_n = 0.96 \text{ W}$
 $S_{R_n} = 5\%$

Inductance (pH/sq)

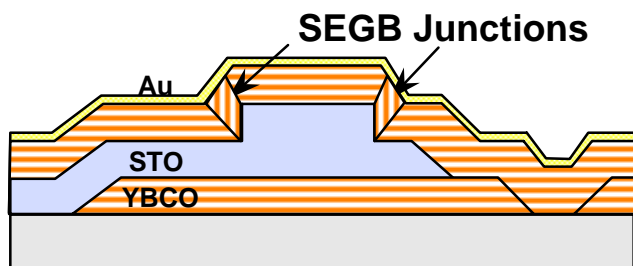


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Integrated HTS Groundplane Required for Low Inductance

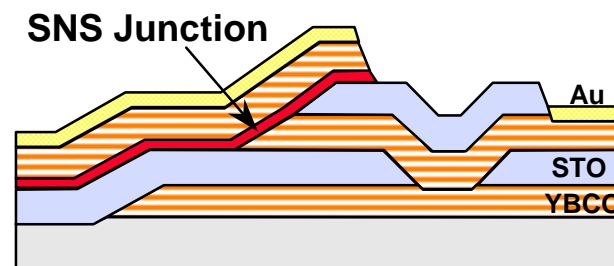
- Achieved for two junction technologies

SEGB Circuit Cross Section



- Simpler process but I_c spread ~ 30%

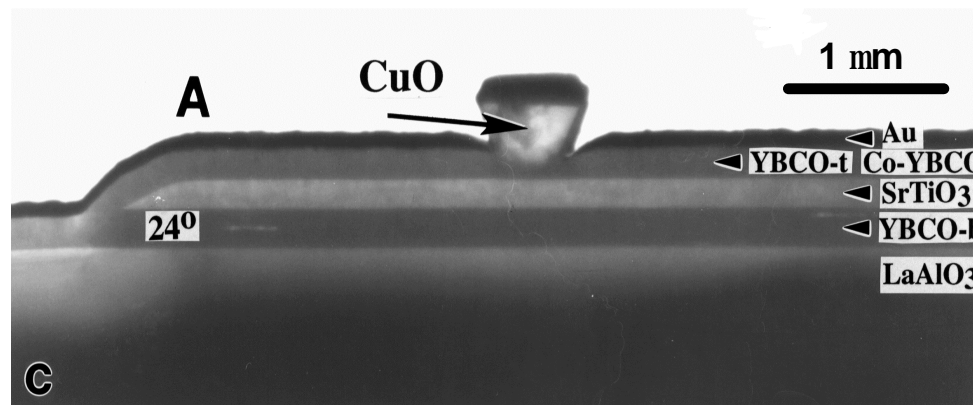
SNS Circuit Cross Section



- More complex process but I_c spread ~ 12%

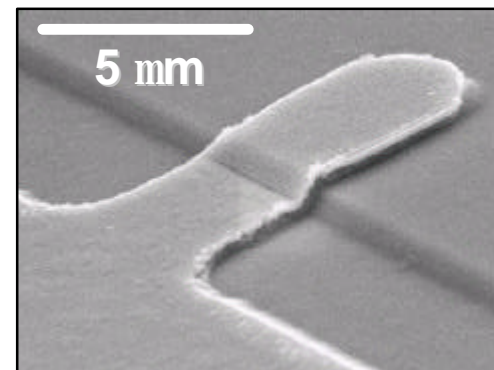
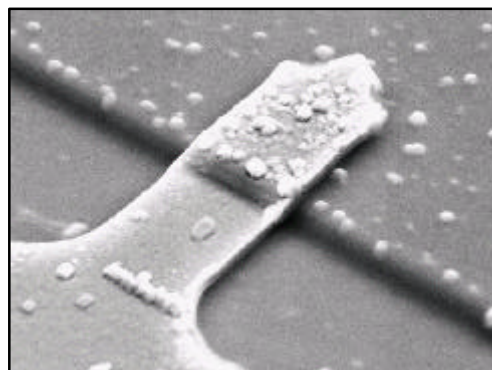
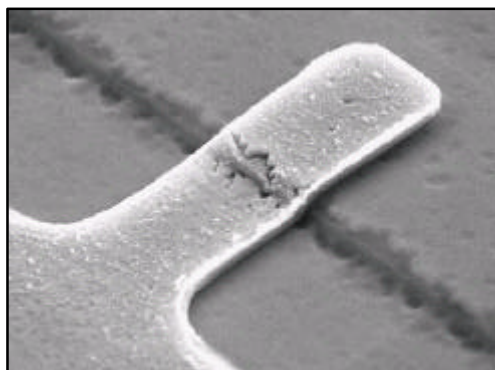
Disadvantage of a Point Compound: CuO “Boulders”

XTEM of a boulder
grown in the top
YBCO layer



Step Coverage

- Top YBCO deposited under three different conditions

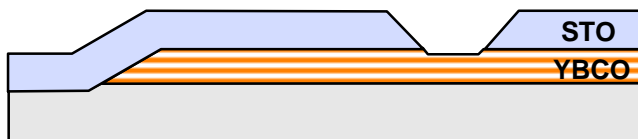


Major Processing Steps for Edge Junctions on a Groundplane

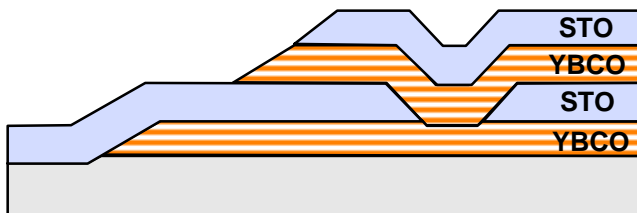
1. Groundplane



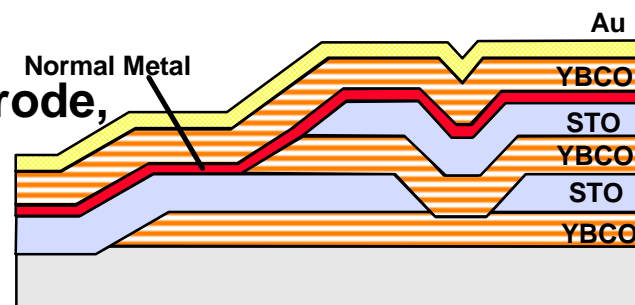
2. Groundplane Insulator



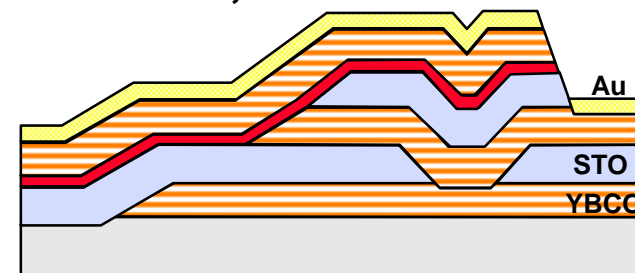
3. Base Electrode / Insulator Bilayer



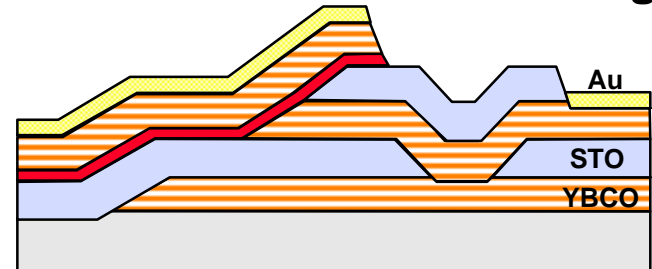
4. N-Layer, Top Electrode, Contact



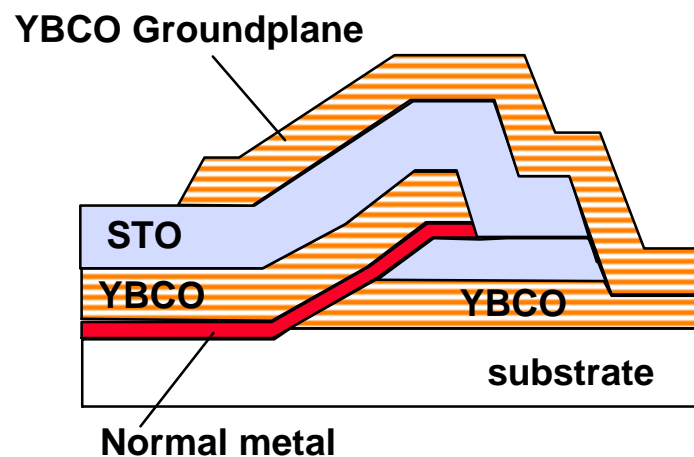
5. Via Holes, Ex-situ Contacts



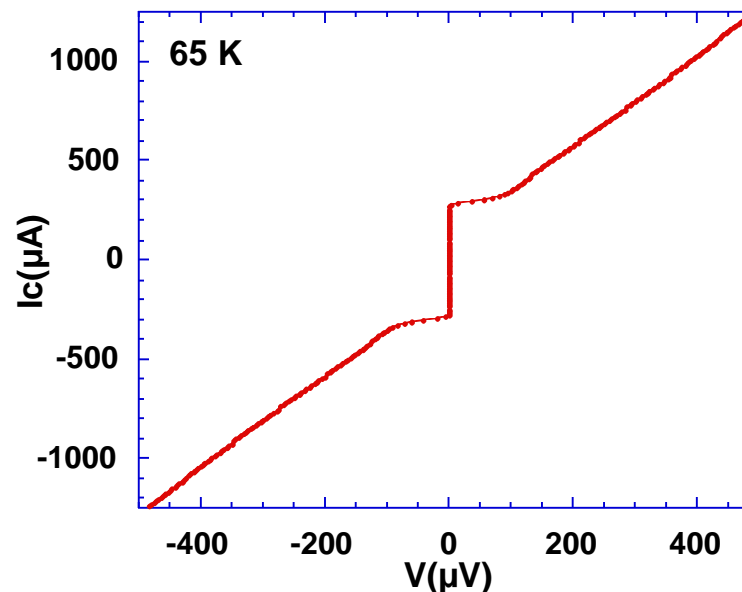
6. Counterelectrode Patterning



Alternative Configuration Tested: Groundplanes on Top



- **Potential Advantages:**
- **Simplified, more forgiving process**
- **Tighter junction spreads**
- **Passivation**



- **High quality I-V characteristics, - same as control chip without groundplane**
- **Junctions survived high temp. processing**
- **Groundplane effectiveness under study**

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Control of SNS Junction Resistance

- High R_n for HTS digital circuits, ~ 1 W
- Low R_n for D/A converters, ~ 0.01 W
- In either case, good fit to proximity effect model

Resistance depends on effective area:

- Conduction is uniform by $I_c(B)$ and I_c spreads

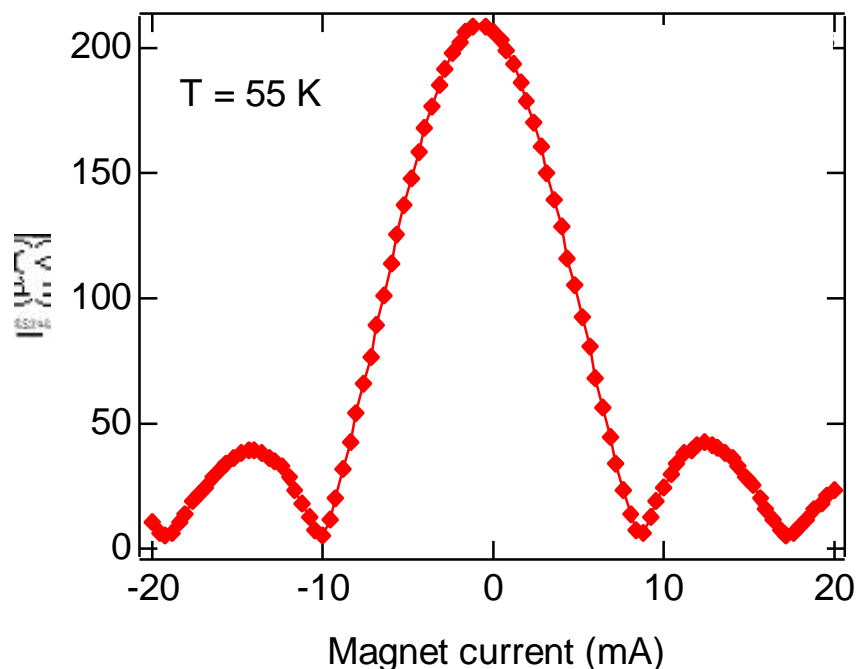
To increase R_n :

- N-layer composition: Higher Co-content
- Thicker N-layer
- Shallower edge angle
- Base electrode composition:
 - La-doping \Downarrow higher R_n than 1:2:3 YBCO
 - sputtered 1:2:3 \Downarrow higher R_n than PLD 1:2:3
- Cleaning of base electrode edge:
 - Br etch \Downarrow 3-5x lower R_n than ion milling
- Deposition parameters of N-layer and top electrode

These factors apply even without N-layer

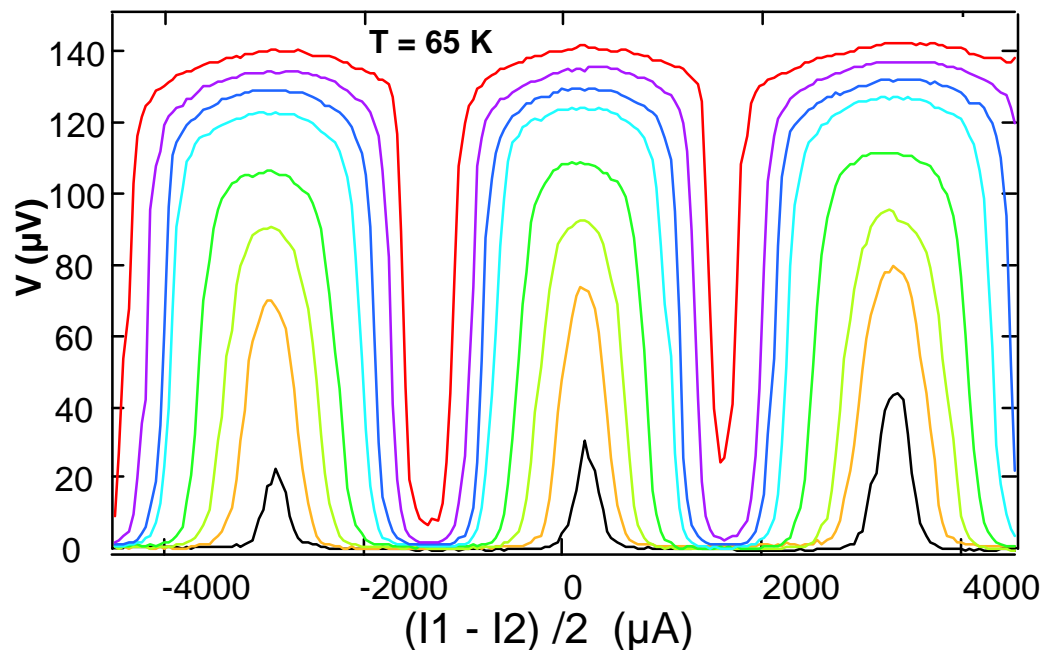
Expected Behavior Observed for Modulation in Magnetic Fields

Single-Junction $I_c(B)$



- Nearly ideal $I_c(B)$ modulation suggests uniform current density **on the scale of the junction area** – may be inhomogeneous on a much finer scale

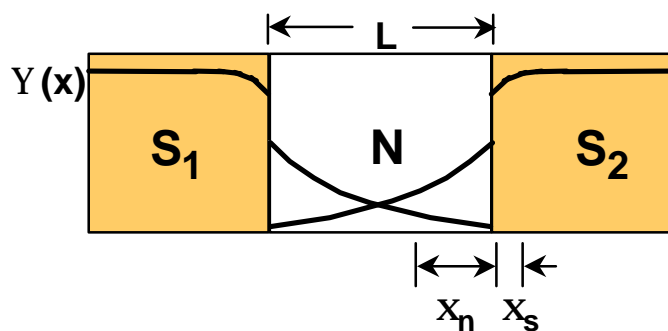
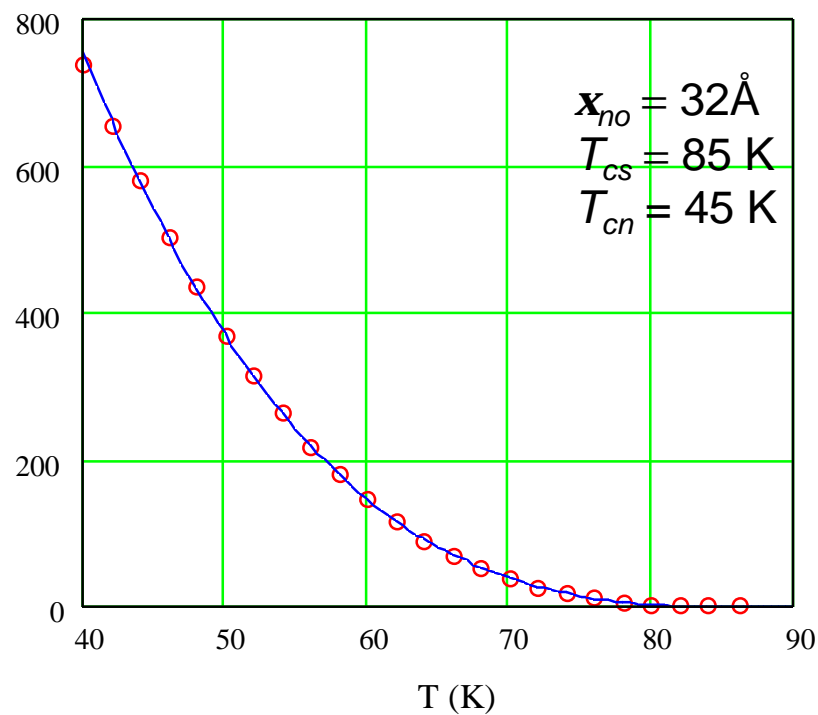
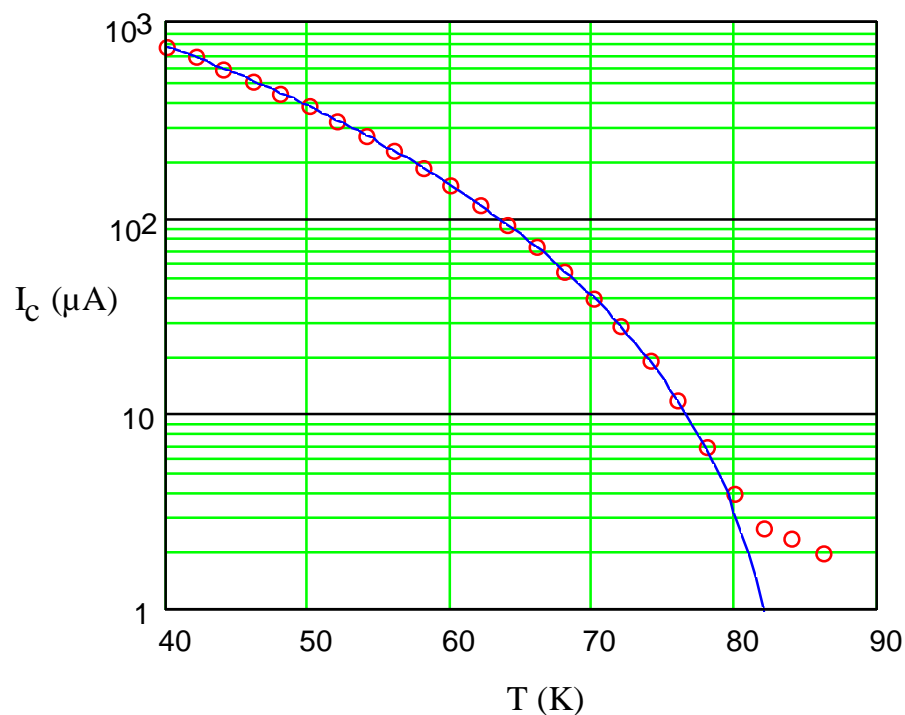
SQUID Voltage Modulation



- Voltage modulation up to 135 μ V at 65 K
- Microstrip inductance ~ 1 pH / sq. at 65K – suitable for SFQ circuits
- Total SQUID inductance as low as 4.5 pH

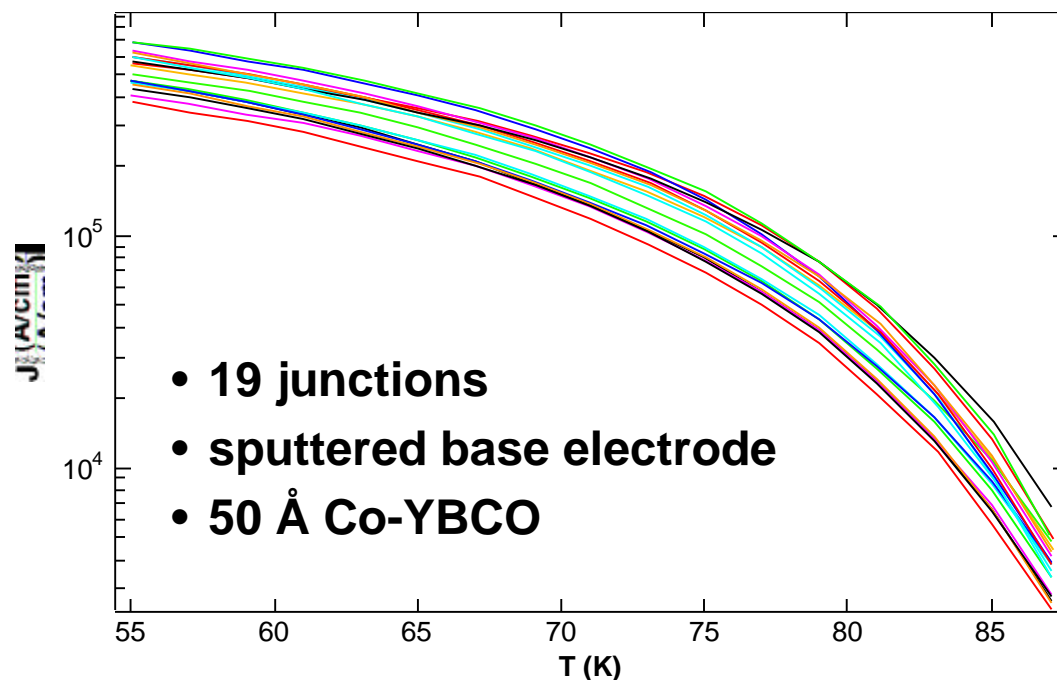
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$I_c(T)$ Fit to Proximity Effect Model Demonstrates SNS Behavior



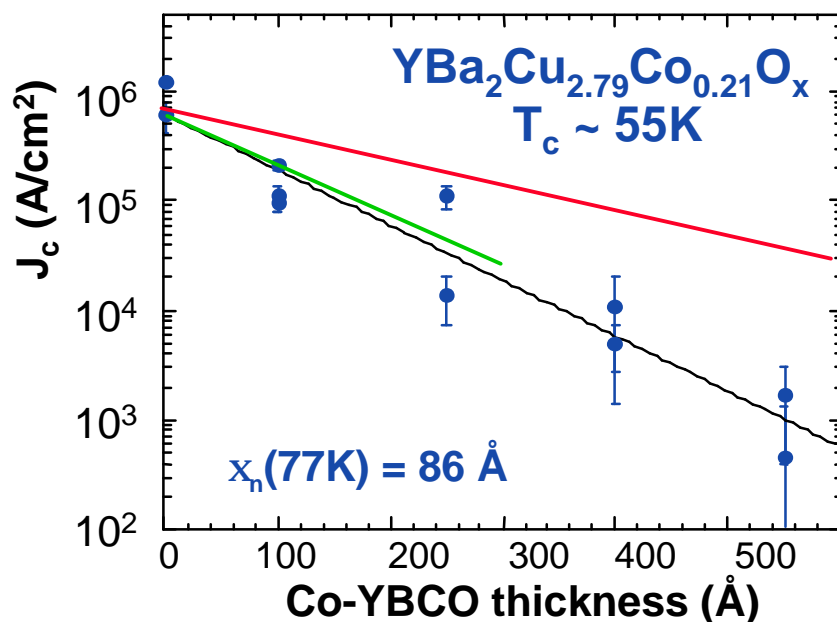
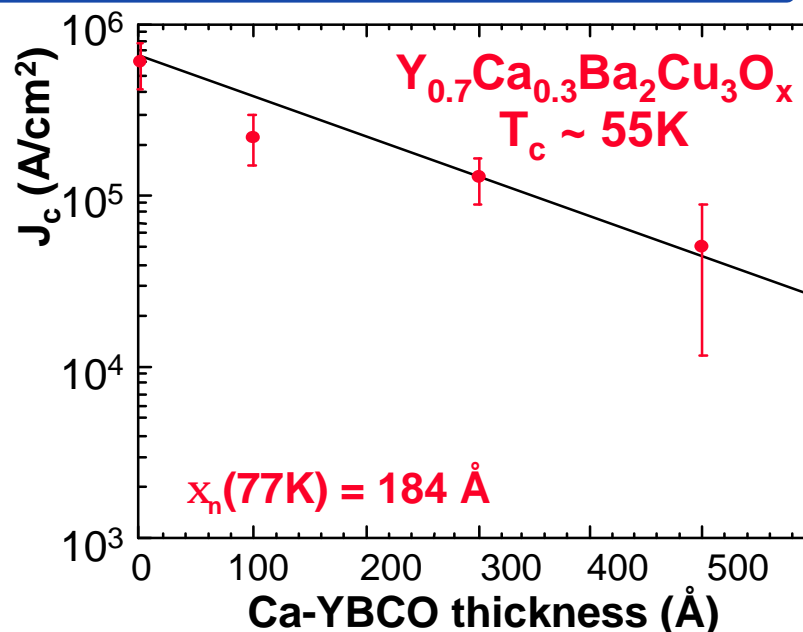
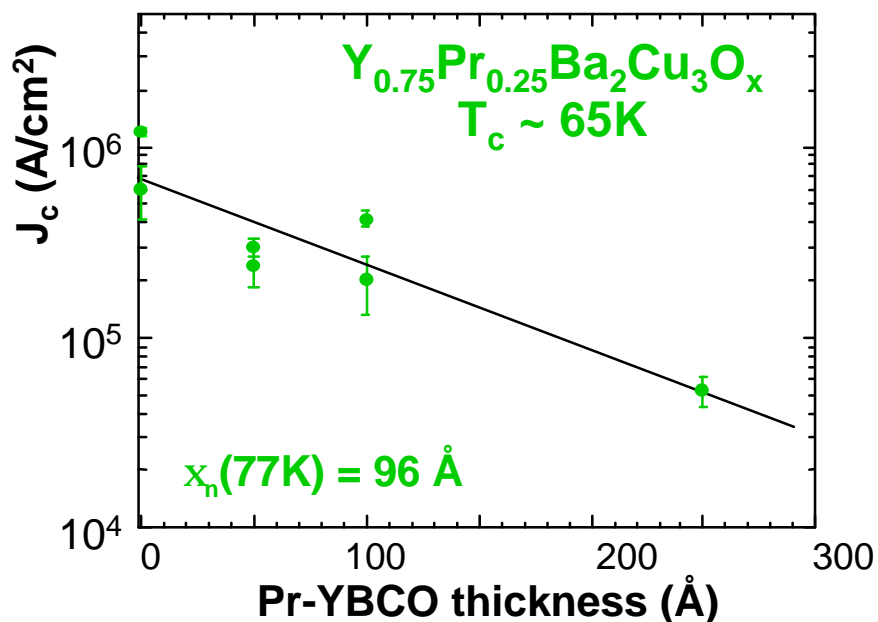
- Fits proximity effect model despite high resistance ($\sim 1 \text{ W}$)
- I_c vs N-layer thickness also fits model

Temperature Dependence of Critical Currents



- Curves tend to have same shape for all devices \Rightarrow suggests area variations predominant, rather than coupling across N-layer
- Requires interface resistance which does not significantly decrease inherent $I_c R_n$:
 - Patchy interface resistance to reduce the active area
 - or SINS (not SINIS) \Rightarrow e.g. insulator on base electrode edge

Exponential Behavior Observed for J_c vs. N-Layer Thickness

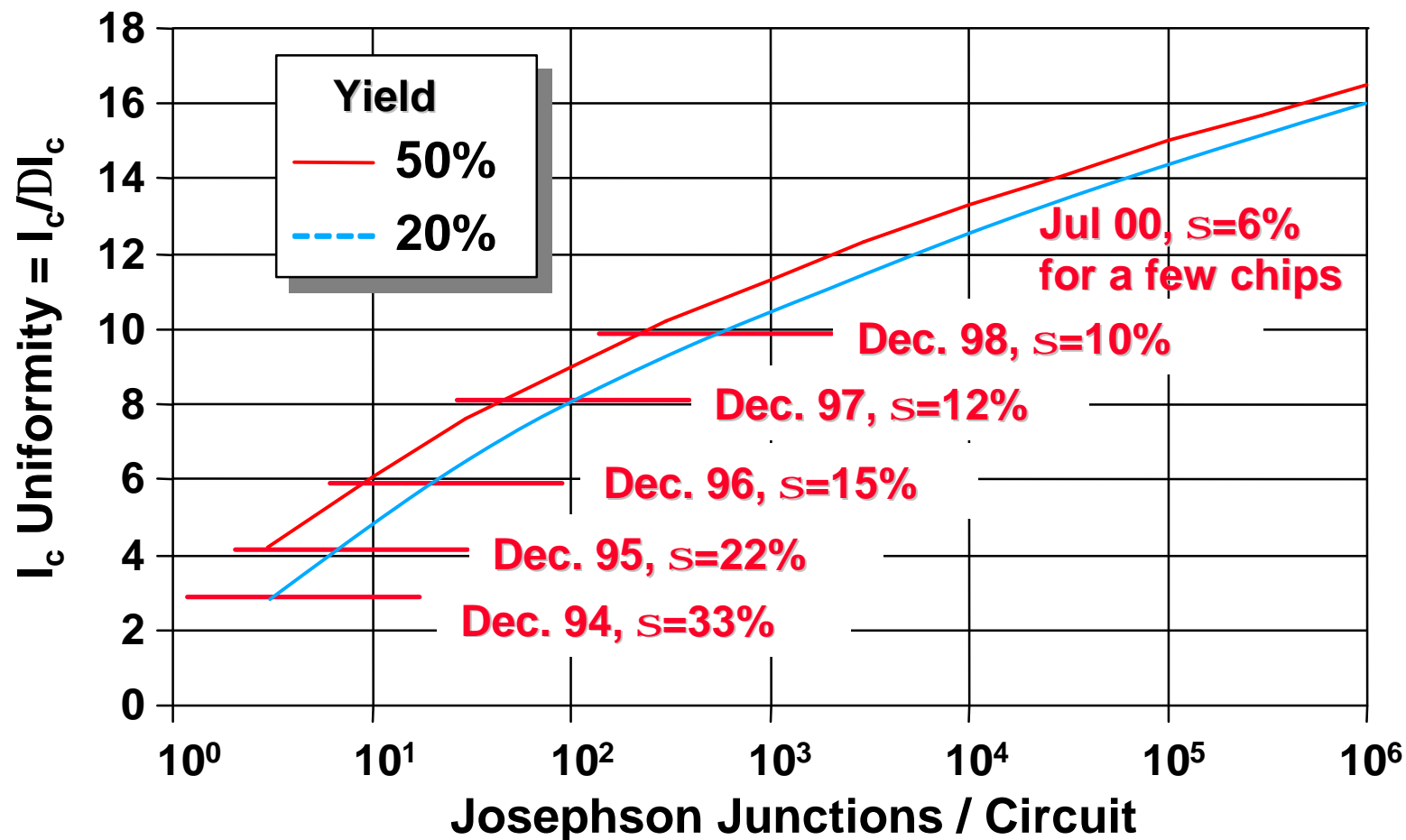


$$J_c \propto e^{-L/x_n(T)}$$

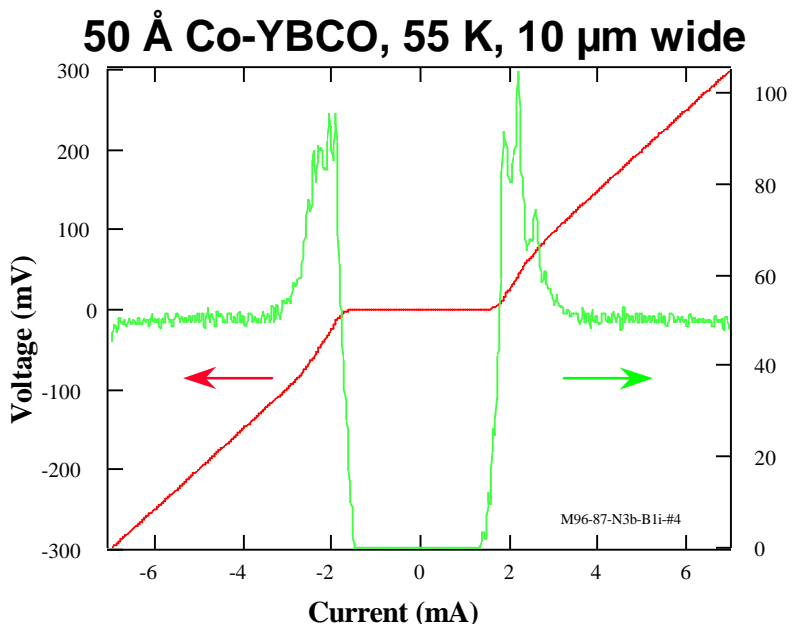
- Exponential behavior predicted by standard proximity-effect model
- Ca-YBCO has longest $x_n(77K)$ consistent with lowest $r(77K)$
- For all N-layer materials, x_n is 5x-10x larger than predicted by r

Continued Long-Term Progress in Junction Uniformity

- Junction uniformity determines the level of circuit integration
- Uniformity defined as inverse of standard deviation

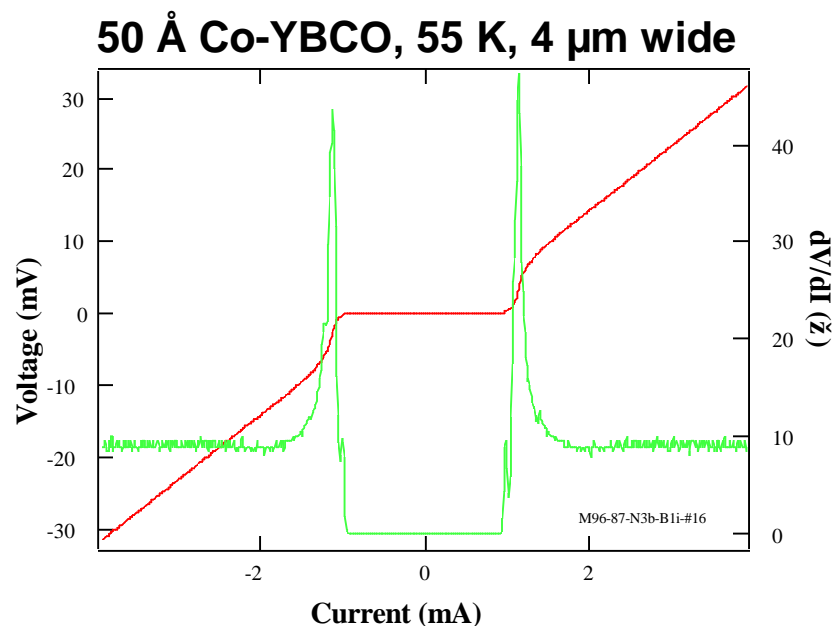


I_c Uniformity in High R_n Series Arrays



**10 junction series array P
with $S_{Ic} \gg 6\%$**

**\ddot{U} 100 junction series array
with $S_{Ic} \gg 11\%$**

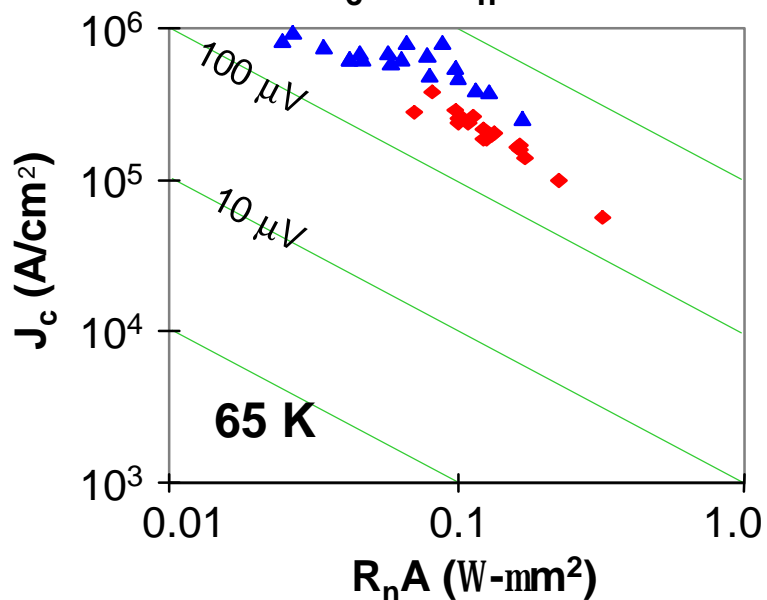


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J_c vs $R_n A$ Scaling for Junctions on a Single Chip

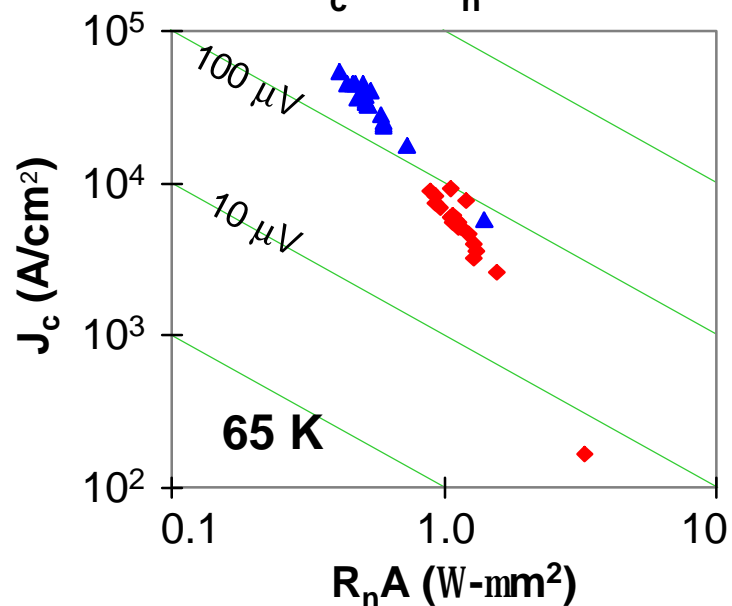
YBCO Base Electrode

J_c vs $R_n A$



La-YBCO Base Electrode

J_c vs $R_n A$



- Constant $I_c R_n$ indicates
 1. Tunneling (SINS) with variations in barrier width or
 2. Reduced junction area with variations in effective area

- Steeper slope in J_c vs $R_n A$ indicates resonant tunneling or hopping conduction
 - What is the physical mechanism responsible for nonuniformity?

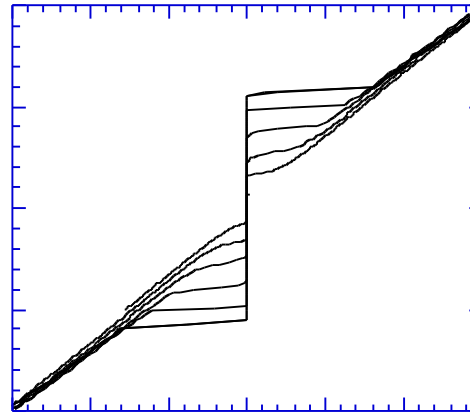
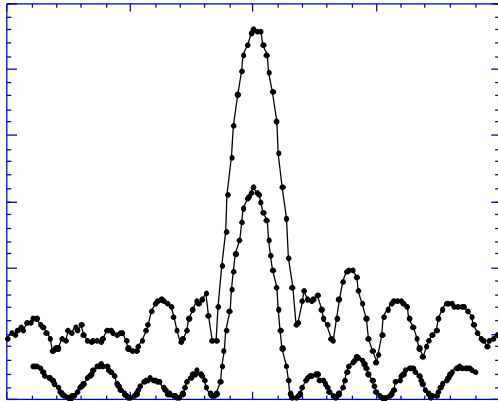
◆ Before plasma anneal
▲ After plasma anneal

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Interface-engineered HTS junctions

Advantages

- Uses intrinsic properties of YBCO
- $R_n A$ tunable over 2 orders of magnitude
- Excellent uniformity: $\pm I_c < 8\%$
- No deposited barrier



Disadvantages

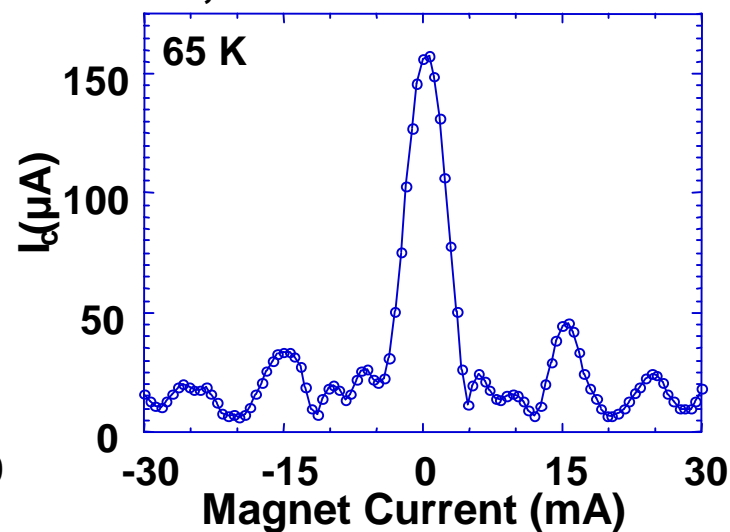
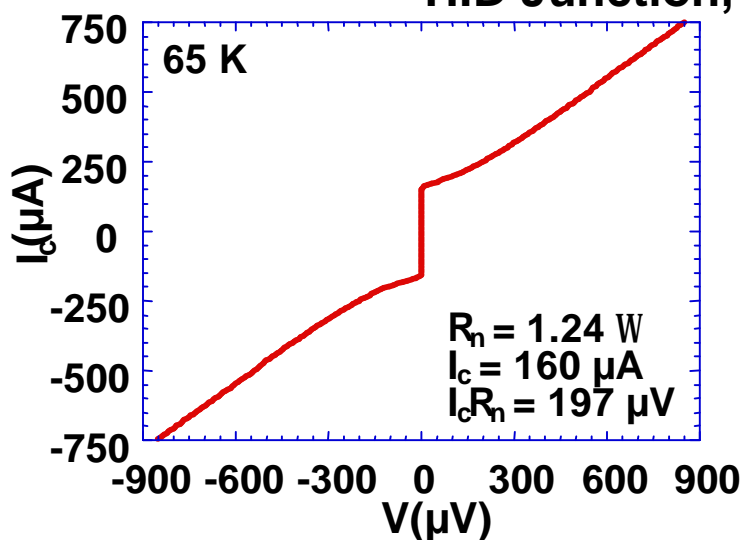
- High- R_n devices not operable at high T
- Not yet good enough for multi-junction circuits

HTS Junctions Formed by Edge Treatment Processes

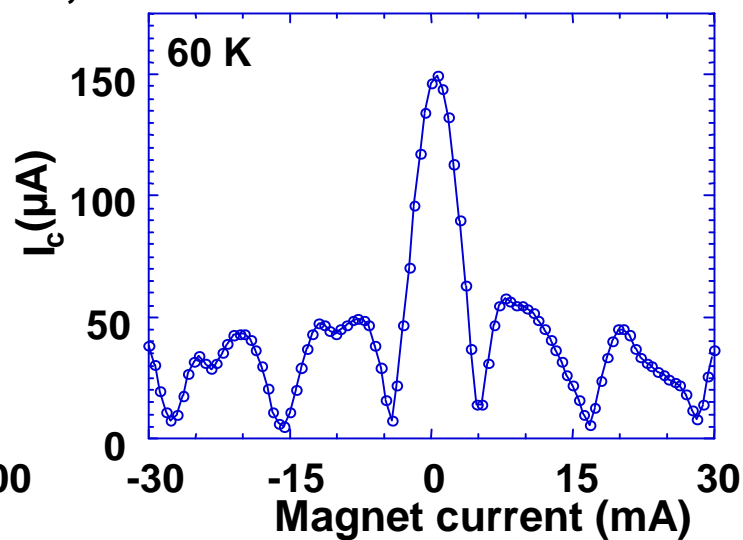
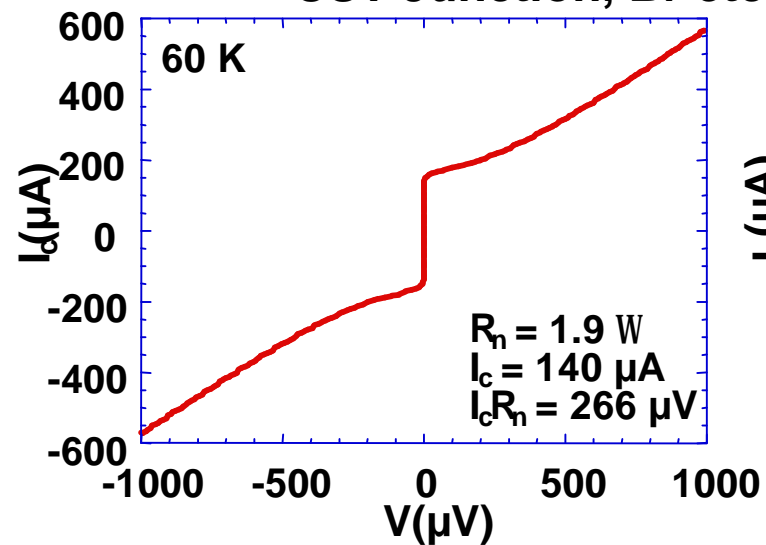
- **Hot-Ion-Damage (HID) based on early JPL work and related to recent hot plasma process of Conductus (“IEJ”) (also Japan, IBM)**
- **Relies on Ar or Xe ion beam to disorder base electrode surface**
- **Basic Hot-Ion-Damage Device (“HID”) Process:**
 - **Standard ex-situ clean (O₂ plasma, Ar/O₂ mill, Br etch)**
 - **In-situ ion mill surface treatment at - 400°C**
 - **3-15 min. at 200V with 5 mA beam is typical**
 - **Ar YBCO mill rate is - 40-50Å in ten minutes**
 - **Vacuum anneal at - 400°C (following Conductus “IEJ” process)**
- **Special case of ion-mill time = 0 is Chemical Surface Treatment (CST)**

IV Characteristics for Edge-Treatment Junctions (no deposited N-layers)

HID Junction, 200 V Ar, 3 min

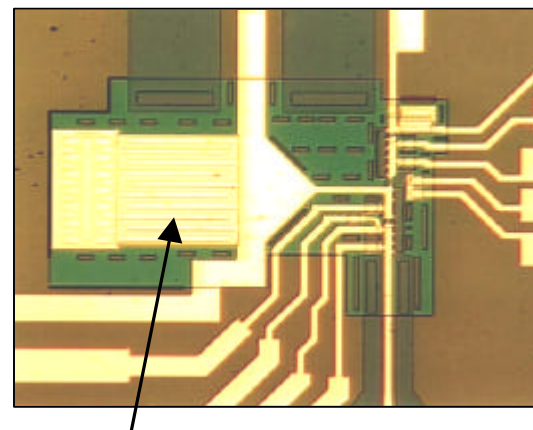


CST Junction, Br etch, 400°C vacuum anneal



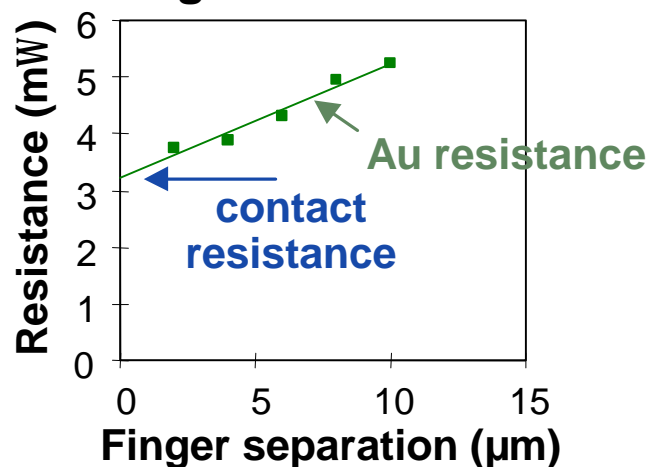
Integrated Resistor Process Developed for Modulator Circuits

- Two resistor ranges required
 - 0.5 -1.0 W / square
 - few mW
- Ti / 0.2 μm Au bilayers on *in-situ* Au meet both requirements
- YBCO / *in-situ*-Au contact resistance determines low-R values

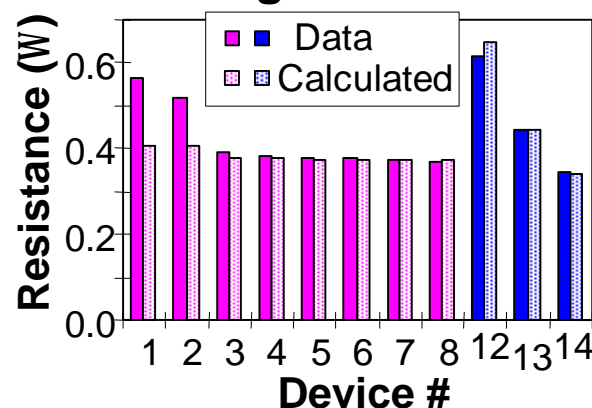


Interdigitated mW input resistor

Resistance vs. length for interdigitated resistors

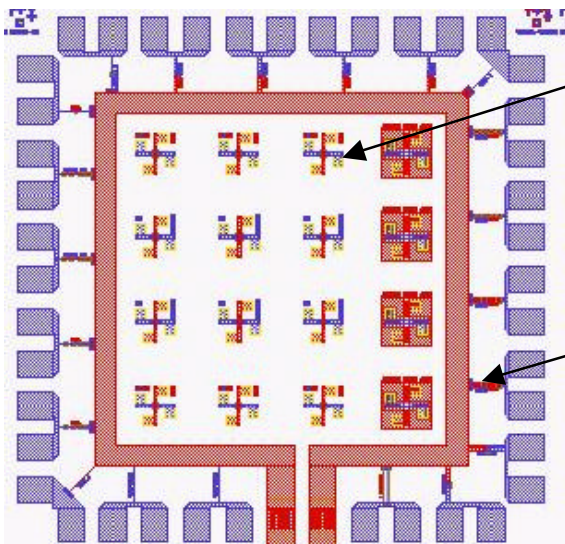


Resistance vs. contact area length and width



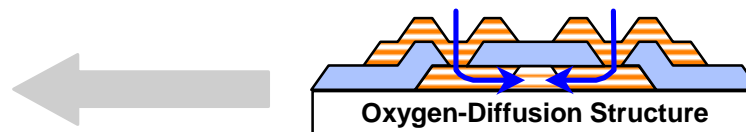
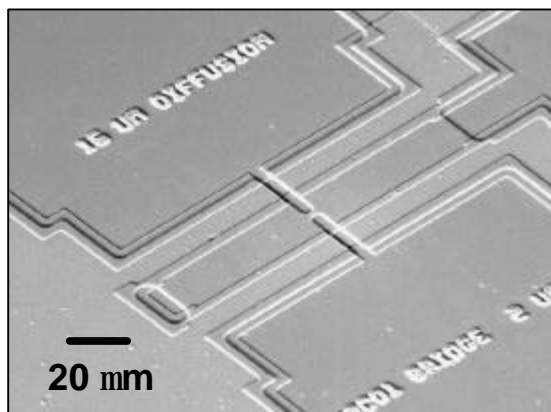
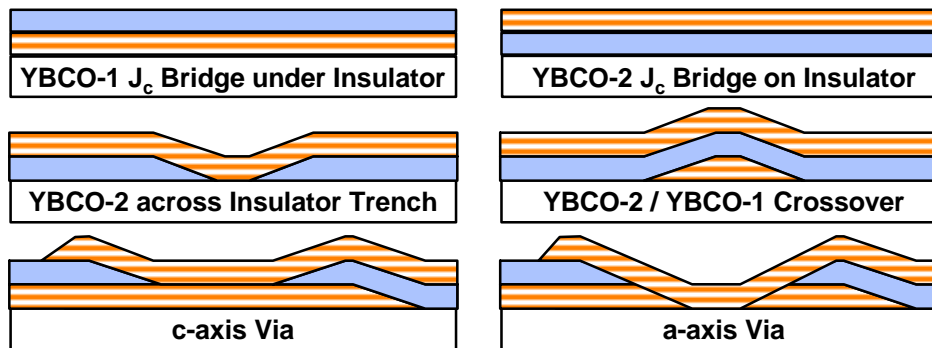
Via, Xover, & Step-Coverage Test Devices Designed, Fabricated, & Evaluated for HTS Circuits

44-Pin Test Sub-chip (1 of 4 per chip)

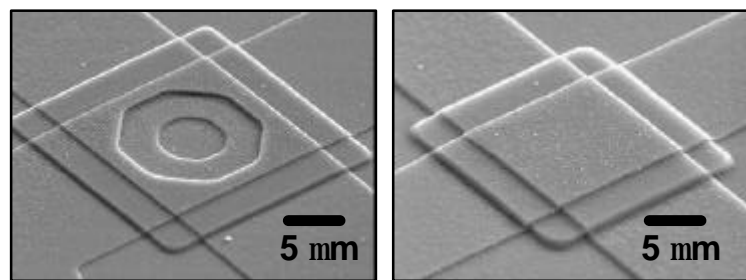
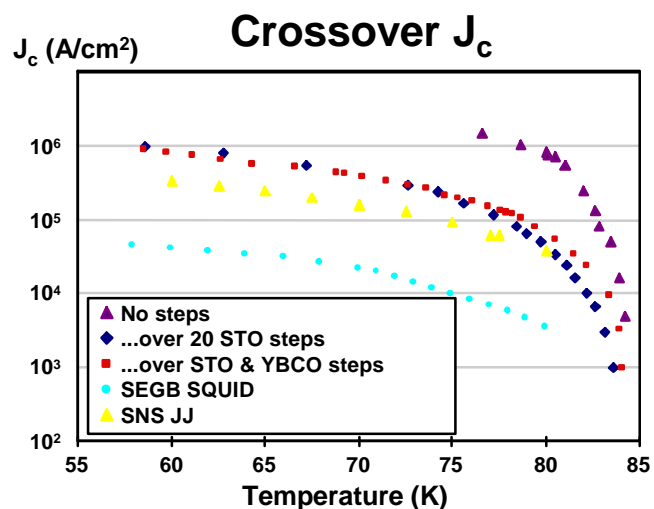


Probe Station Meas:
 10^4 mm² capacitors
and isolation meas.

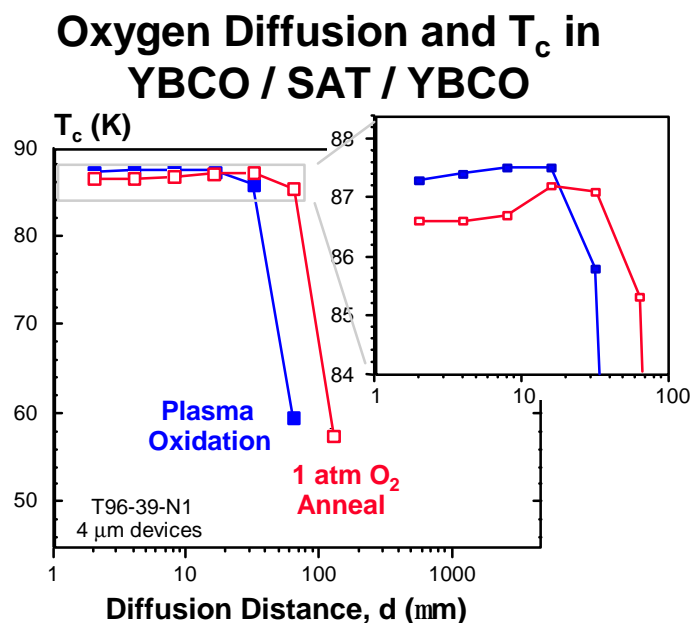
Individual Test Bridges:
single & series
vias & Xovers



Accomplishments: Processes Developed for Crossovers, Vias, and Oxygen Diffusion

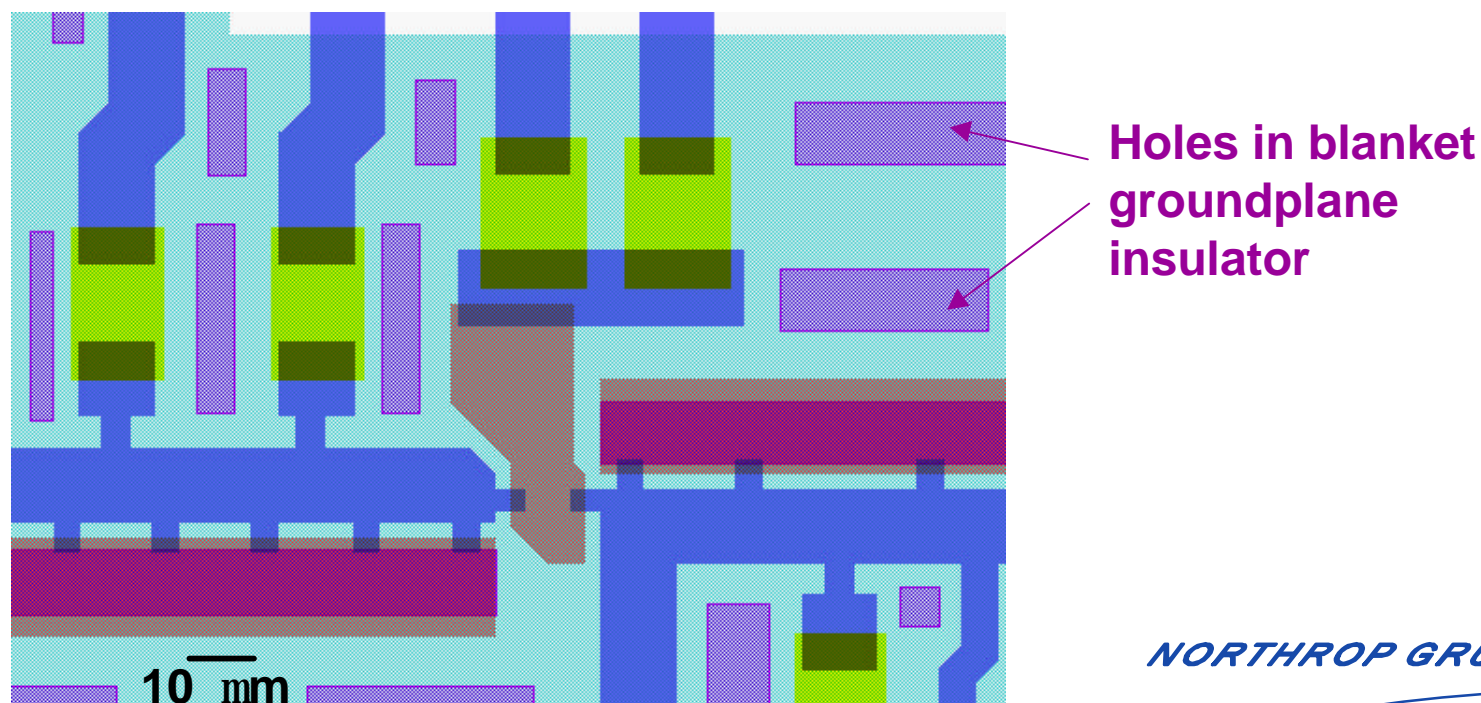


- Critical currents for passive devices, $J_c \gg$ junction critical currents
- Low- ϵ , low-tan δ SAN and SAT insulators replacements for STO
- a-b plane oxygen diffusion measurements determined coef
 - 7×10^{-9} cm²/s, in agreement with literature values for single crystals --- impractical times
 - invention of “oxygen vias”



Innovations Used for Modulator Circuits: Mask Layout with “Oxygen Vias”

- With improvements in YBCO film smoothness and insulator integrity, even 4-day oxidation anneals at 450°C cannot restore $x = 6.90-6.95$ in YBCO_x ground planes
- Cooling in oxygen plasma provided solution before changeover from SrTiO_3 to SAN and SAT insulators
- Measurements of a-b plane oxygen diffusion rates in films agreed with single crystals and determine “oxygen via” spacing and oxidation times

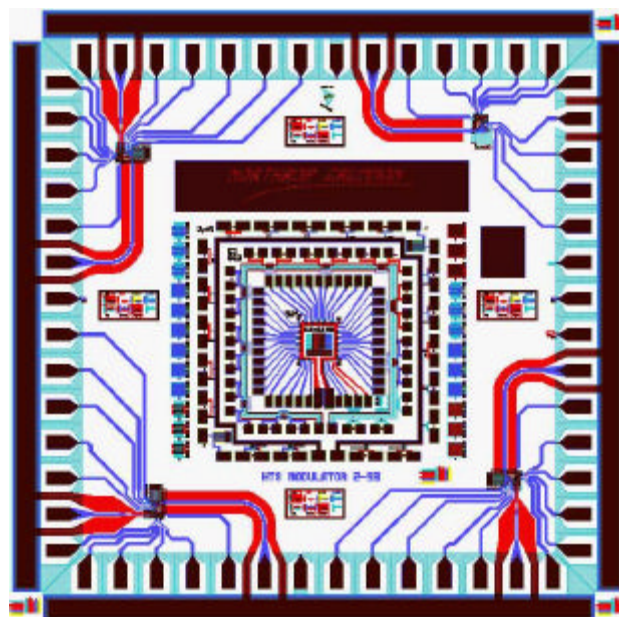
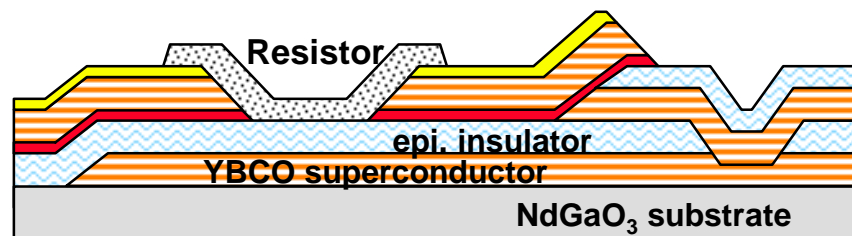


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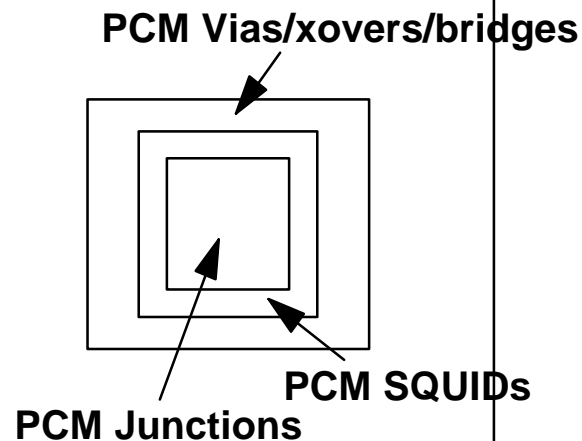
Approach: Same Chip Dies Couple Circuit Development to Process Development

- Multiple circuit copies to experiment with component values and layout parameters
- Multiple PCM subchips for process development

Circuit Cross Section

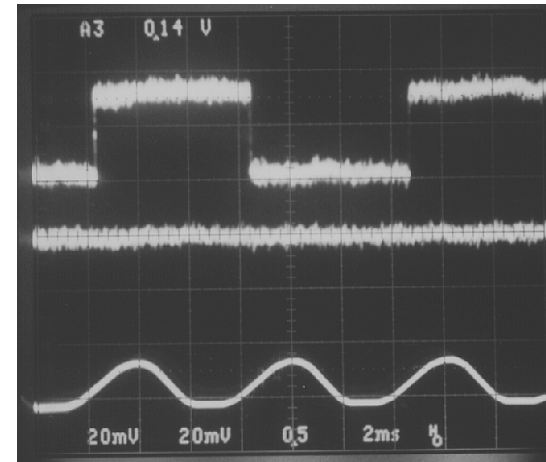
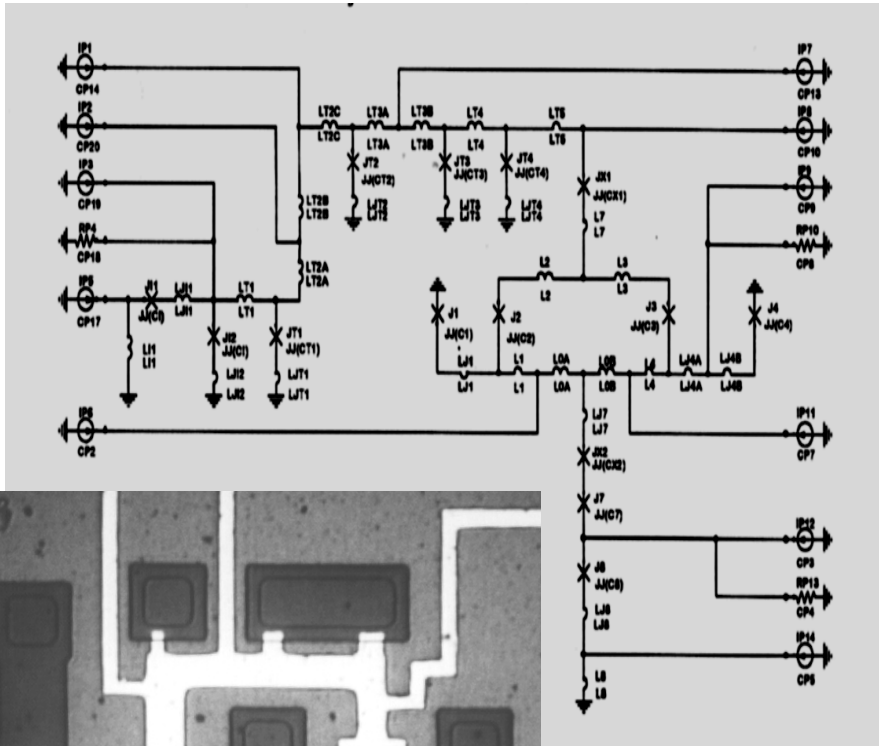


Circuits

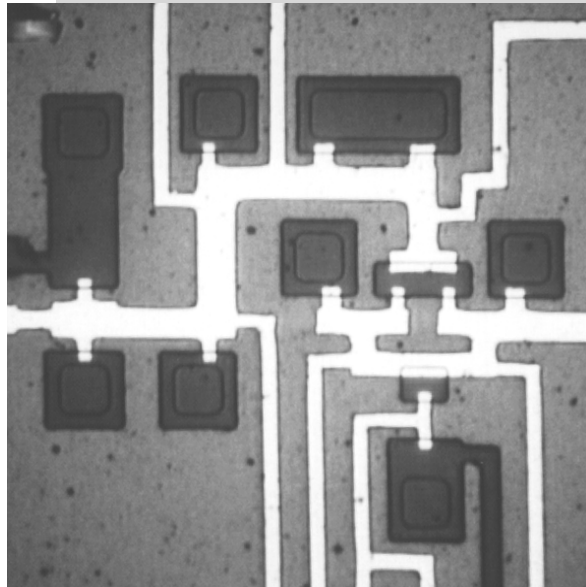


HTS SFQ T-Flip-Flops Operate at 65K

Satyr T-FF



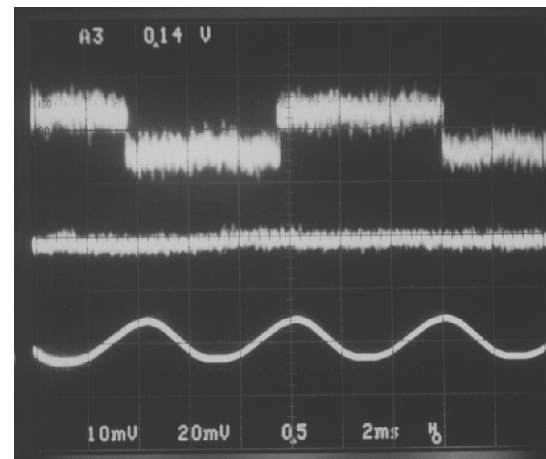
Readout
FF Voltage
SFQ Gen Input



T-Flip-Flop

- Satyr
- Triton

Triton T-FF

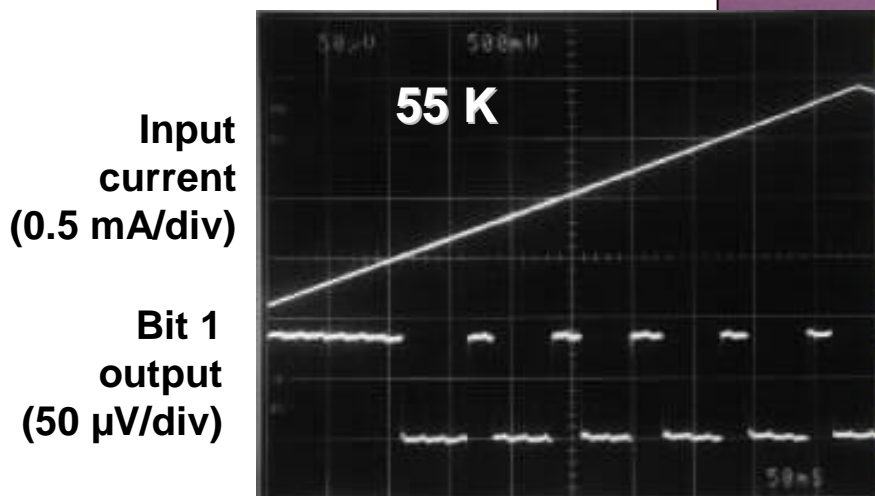
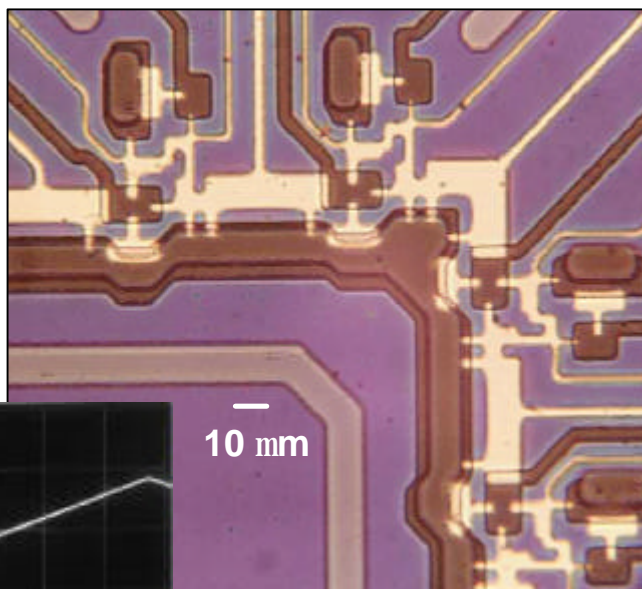
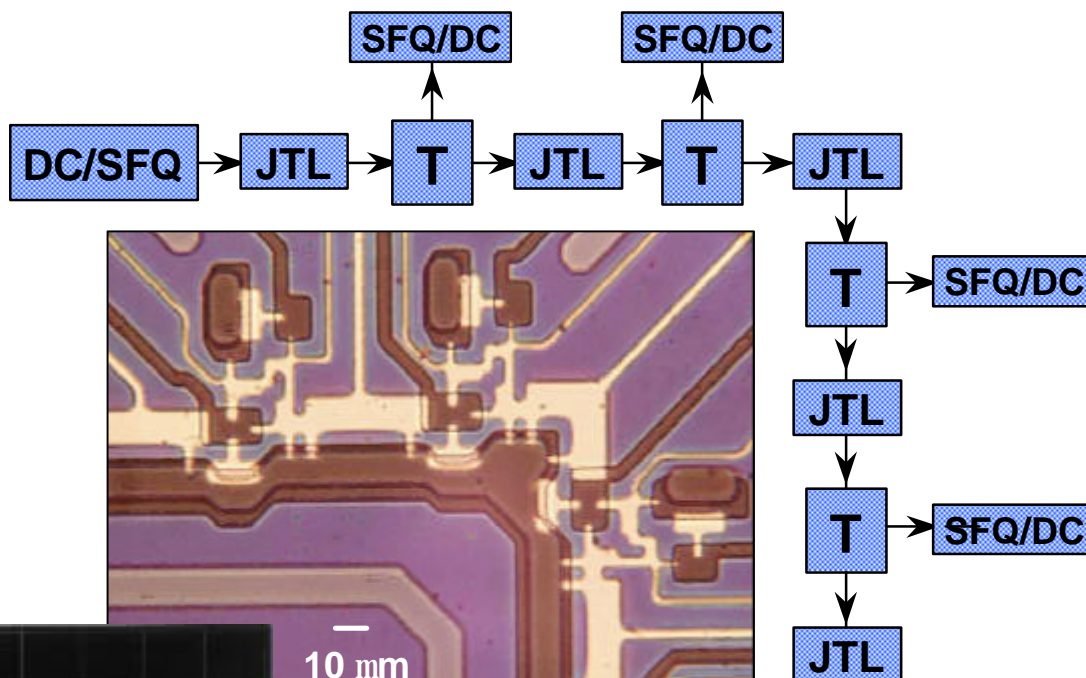


Readout
FF Voltage
SFQ Gen Input

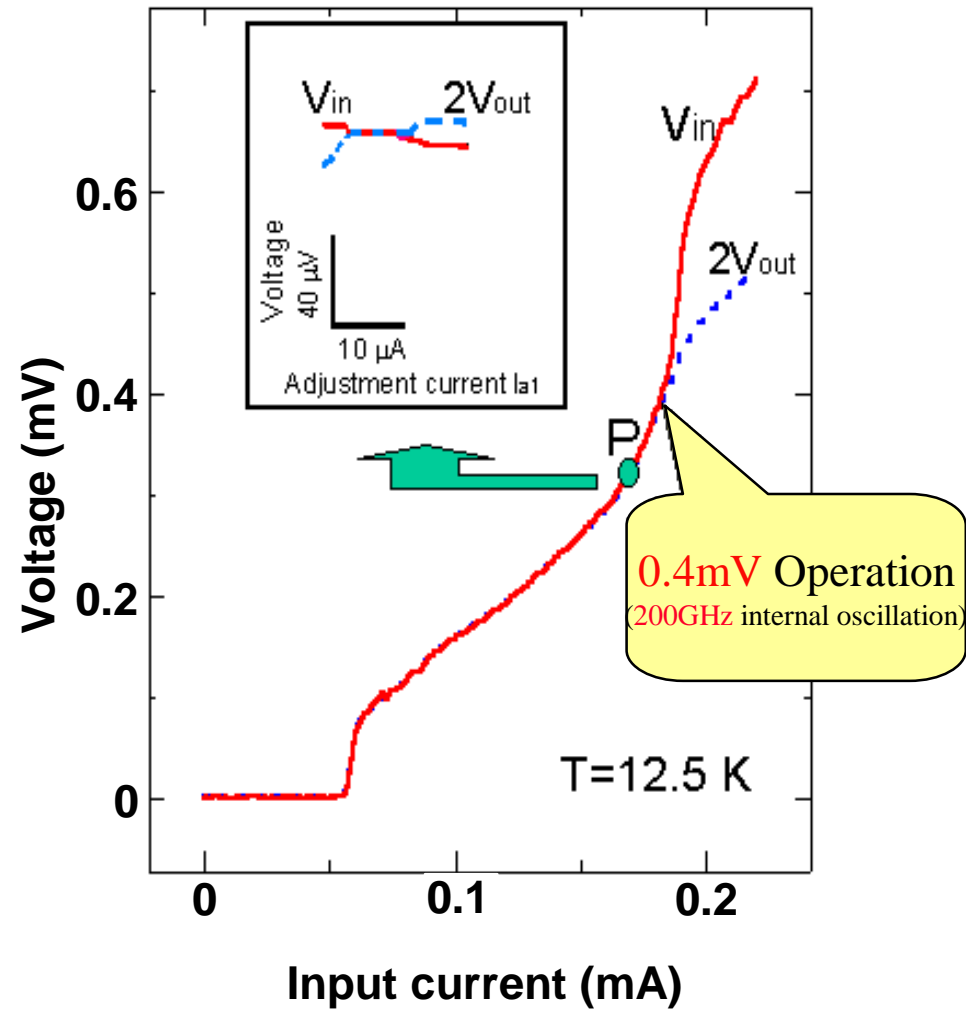
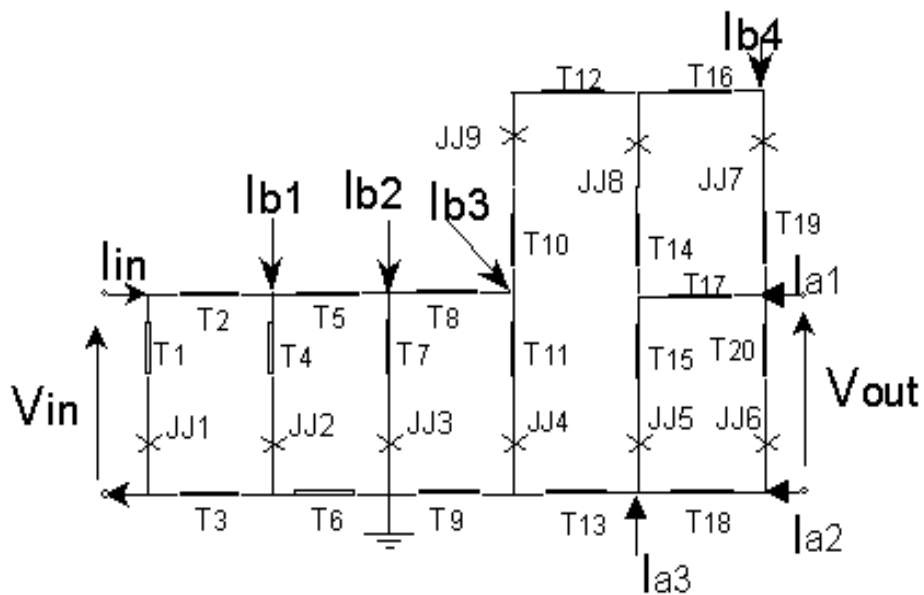
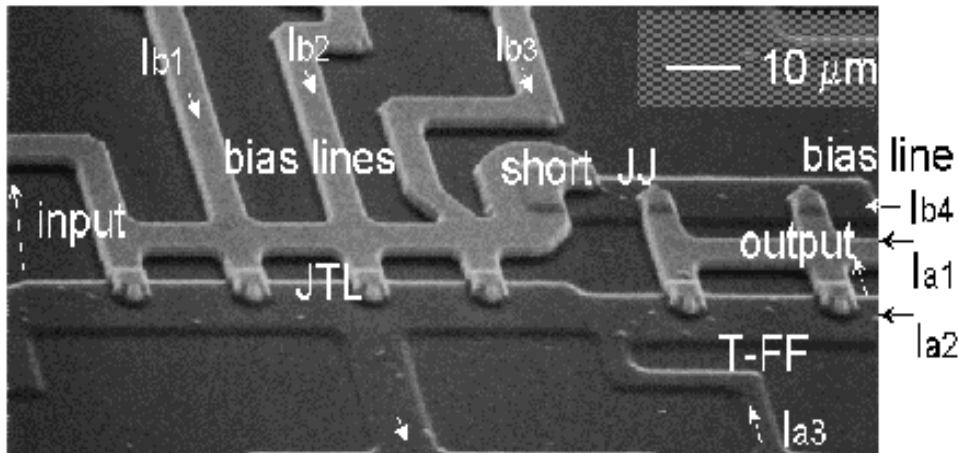
(Dale Durand, TRW)

4-Bit Counting A/D Converter for Low-Power Operation

- 39 junction circuit fabricated with extendible process
- All four T flip-flops can store flux & be read out
- First bit toggles with input current

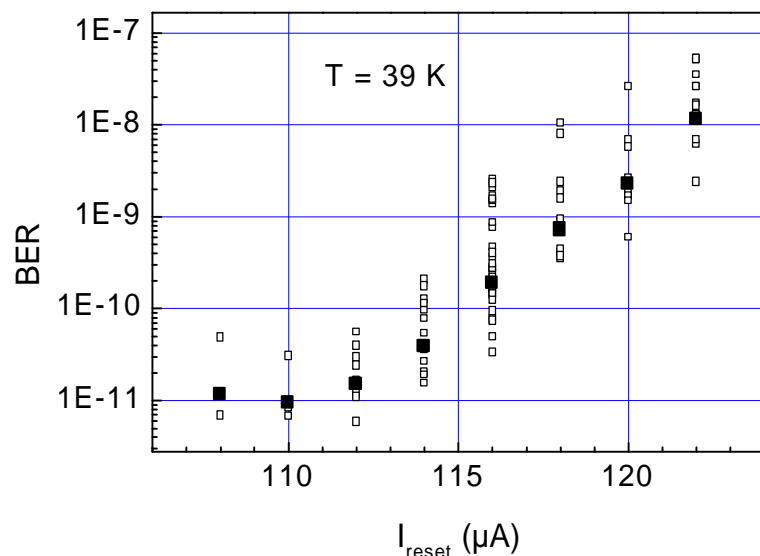


Voltage Divider Utilizing HTS Ramp-edge Junctions with a Ground Plane

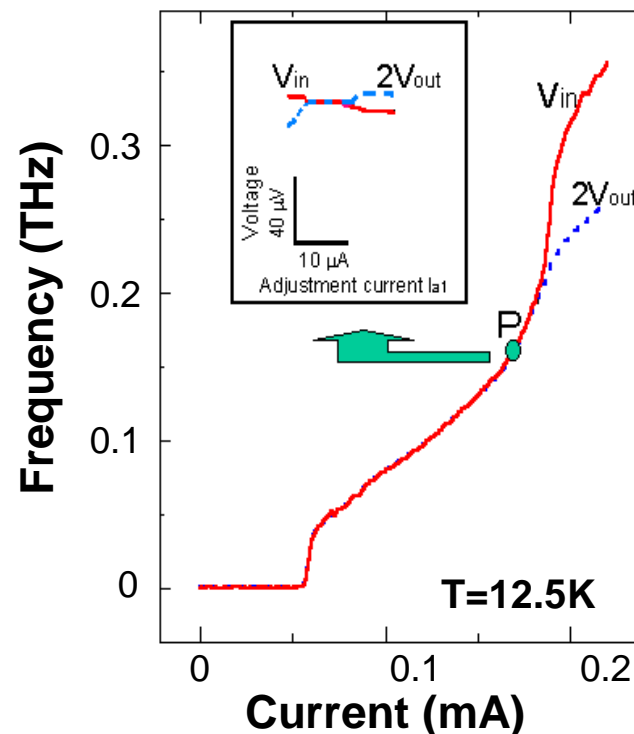
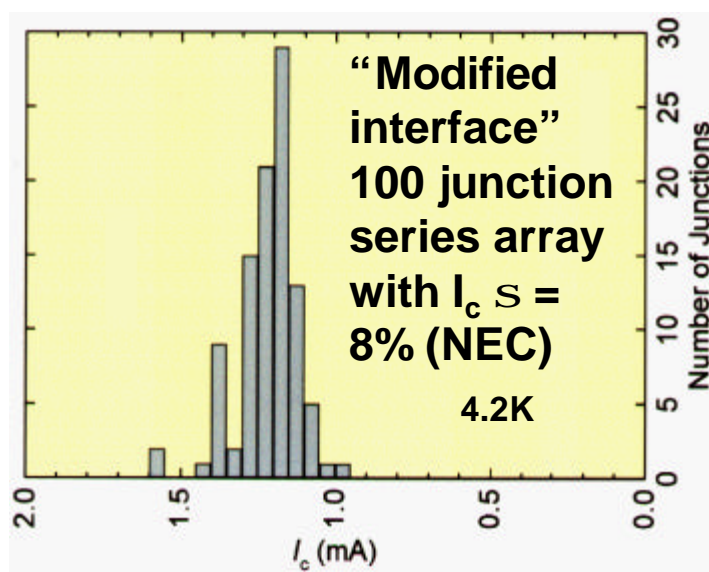


TOSHIBA

Summary of Worldwide Progress in HTS Junctions & Circuits

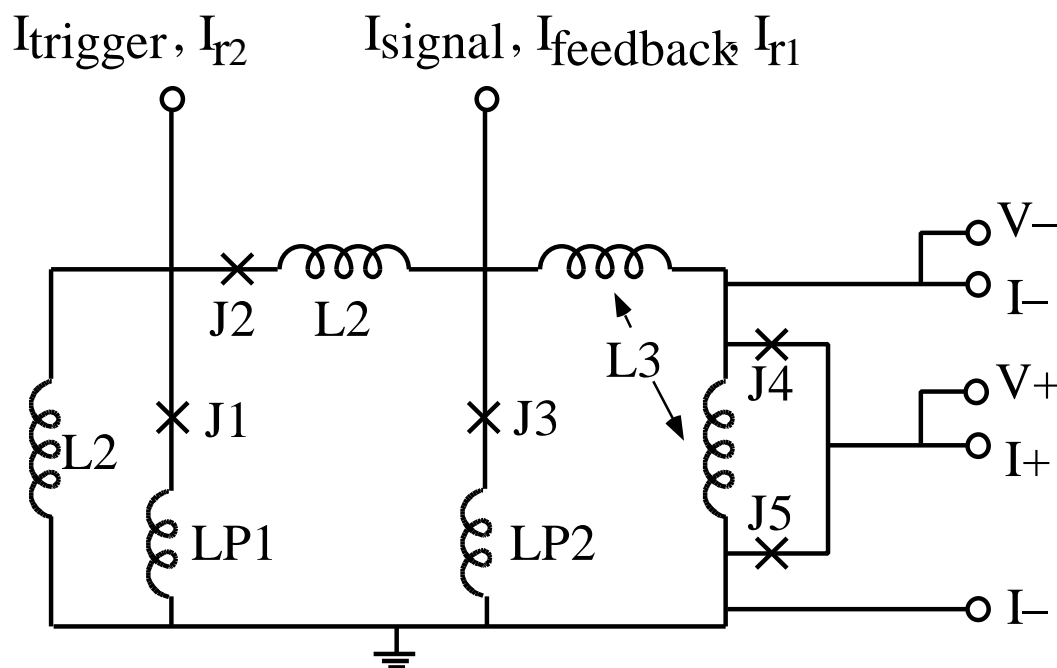


Measurement
of $BER < 10^{-11}$
in HTS at 39K
(KFA Jülich)



Toggle flip-flop @ 200GHz with
extendible process (Toshiba)

HTS Sampler (NEC)



- High $I_c R_n \Rightarrow$ good time resolution
- 60K \triangleright 0.5 mV \triangleright 3.5 ps
2 mV \triangleright < 1ps
- Thermally-limited sensitivity $d \sim 0.15 \mu\text{A}$ @ 60 K
- 50 W \triangleright $dV \sim 7.5 \mu\text{V}$
- GaAs sampler $\sim 100 \text{ mV}$ @ comparable time res.

M. Hidaka & J.S. Tsai, IEEE Trans. Appl. Supercond. Vol. 5., No. 2, June 1995
M. Hidaka, H. Terai, T. Satoh, & S. Tahara, ISEC '97, Paper D54

HTS Technology Enables CRYORADAR™ to Find Targets in Clutter

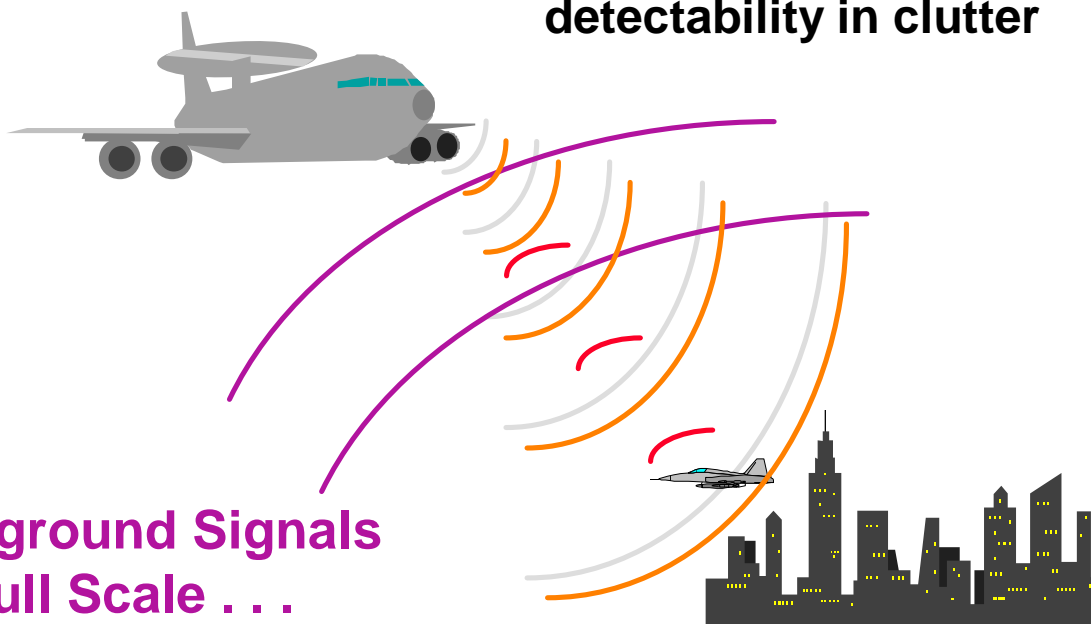
Cryoelectronic Radar Subsystems Provide:

Pure Transmit Signal

- 100x increase in microwave resonator Q
- 50x increase in dynamic range
- 50x reduction in size

Low Noise / High Dynamic Range Reception

- 10x increase in speed
- 10x reduction in power of logic circuits
- ~20 dB improvement in target detectability in clutter



Large Background Signals
Establish Full Scale . . .
but Small Signals Can Be Important

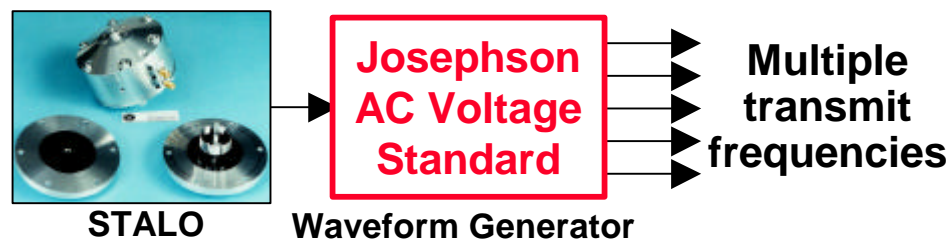
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Josephson-Based Circuits Are Needed to Exploit Low-Phase-Noise STALOs

Cryo STALO

- Significant Improvement in Radar Sensitivity (Limited by state-of-the-art ADC)
- Demonstrated in Navy Radar Testbed
- Integrated cryocooler

Transmit ...



- Avoid jamming
- Track scintillating targets
- Minimum junction count, ~ 100-300

... Receive



- Quantized flux provides linearity in the feedback mechanism of ADCs with S- D architecture
- Junction count, ~ 350-1000

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Digital (Mixed-Signal) Subsystems for CRYORADAR™

Low-noise DACs and High-dynamic-range ADCs

HTS DACs are based on the same physics as the US standard volt and new NIST initiative for ac voltage standards

- Josephson junctions convert frequency of pulses to a voltage level
- **5 GHz** Junction parameters of

$$\begin{aligned} I_c R_n &\gg 10 \text{ mV} \\ I_c &\gg 1 \text{ mA} \\ R_n &\gg 0.01 \text{ W} \end{aligned}$$

HTS ADCs designed in S- D architecture

- Quantization of magnetic flux used for precise feedback
- Switching speed needed for oversampling
- **500 GHz** Junction parameters of

$$\begin{aligned} I_c R_n &\gg 1 \text{ mV} \\ I_c &\gg 0.5 \text{ mA} \\ R_n &\gg 2 \text{ W} \end{aligned}$$

- In Japan, S- D ADCs for “software radio”

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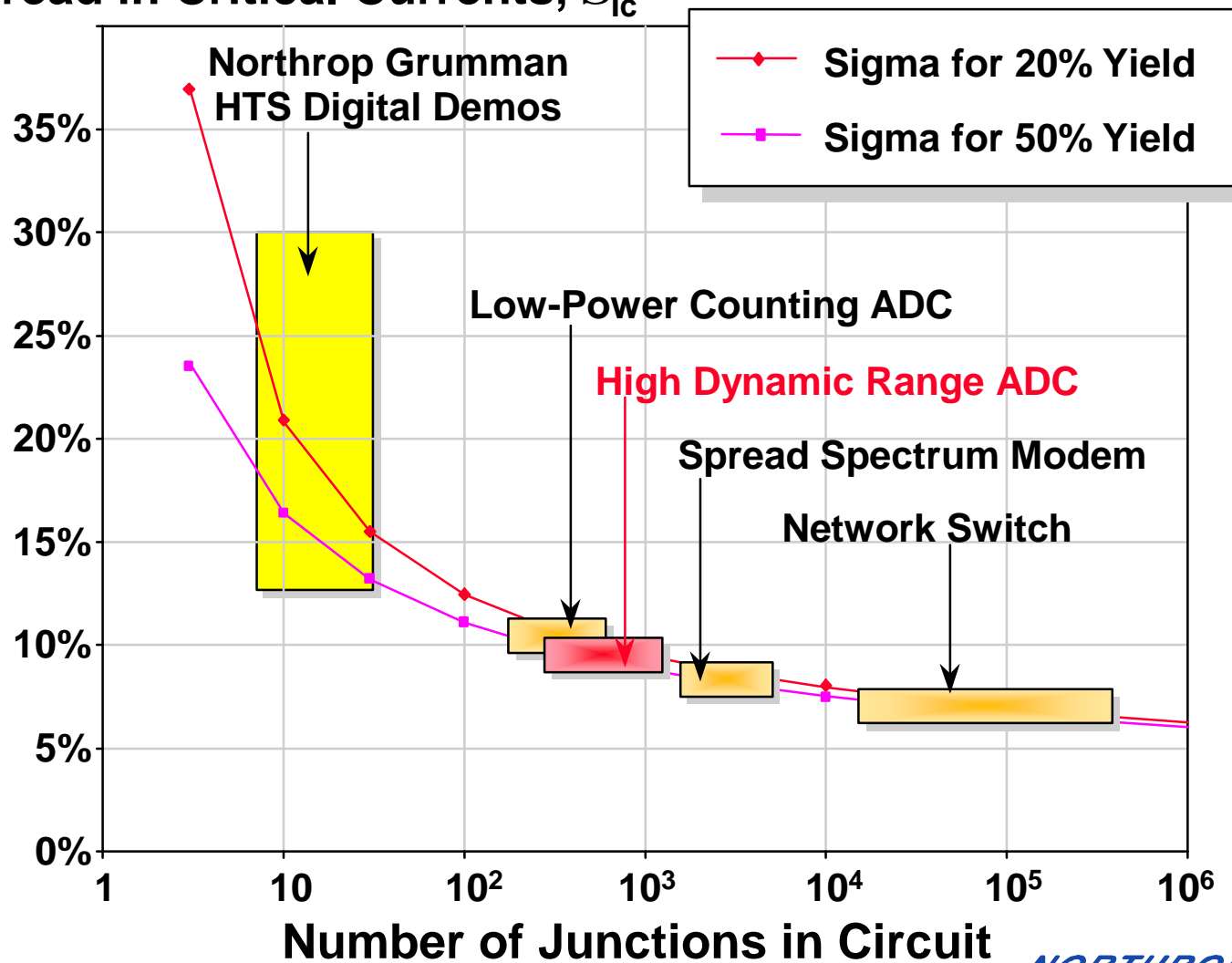


ADCs and DACs: The Right Niche for HTS Josephson Technology

- **Workshop on Superconductive Electronics: Devices, Circuits, & Systems, 9/97, CMOS working group:**
 - *“Deeply scaled CMOS not likely to support high-dynamic-range ANALOG functions ...”*
- **ADCs and DACs are principally analog circuits**
 - Precision tracking/generation of analog signals
 - Bit error rate requirements modest ($< 10^{-6}$)
 - Junction count \ll e.g. processors
- **Use properties unique to superconductivity**
 - Flux quantization
 - ac Josephson effect

Junction Non-Uniformity Motivates Applications with Low Junction Counts

Spread in Critical Currents, S_{Ic}

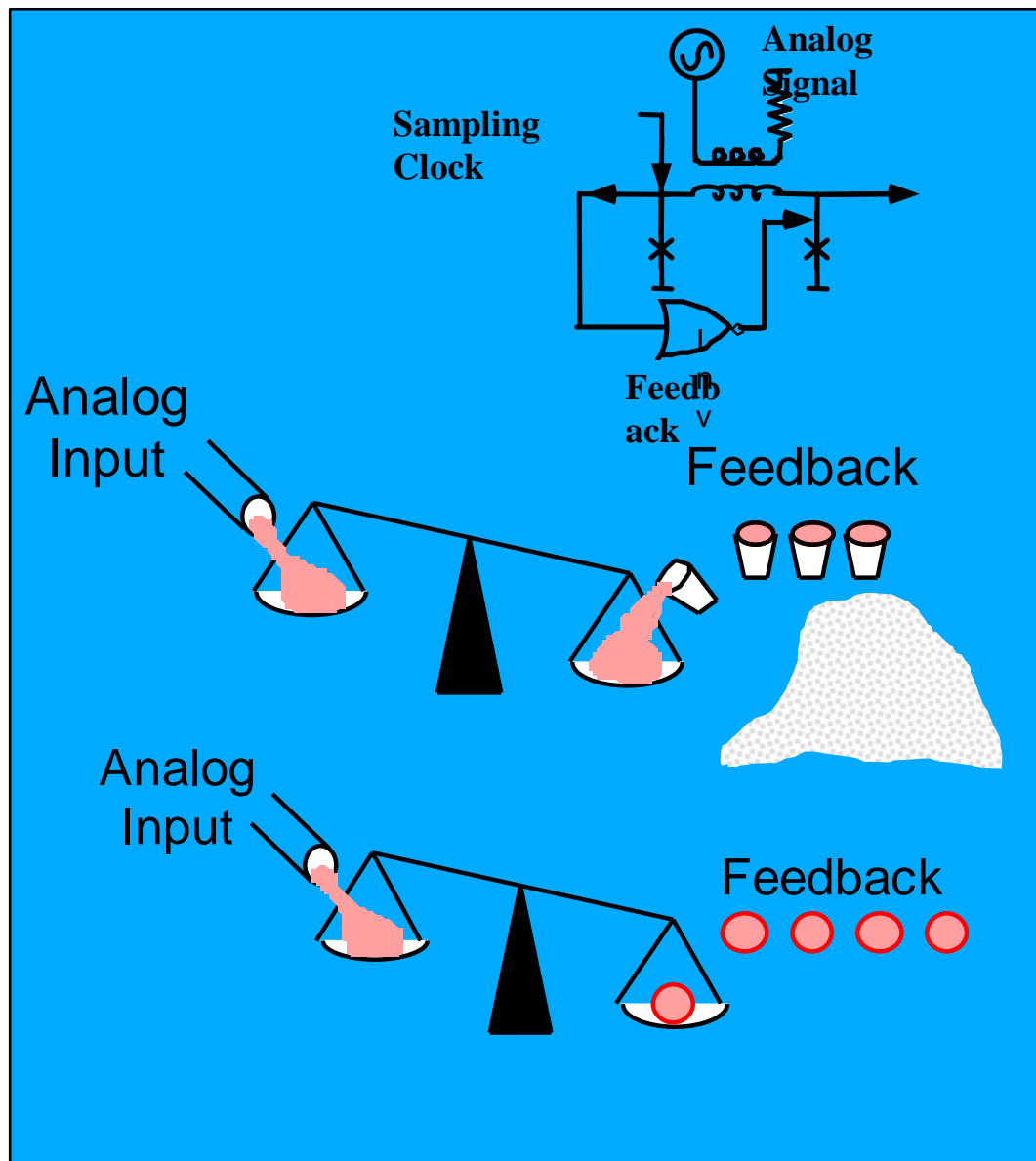


Northrop Grumman's Approach

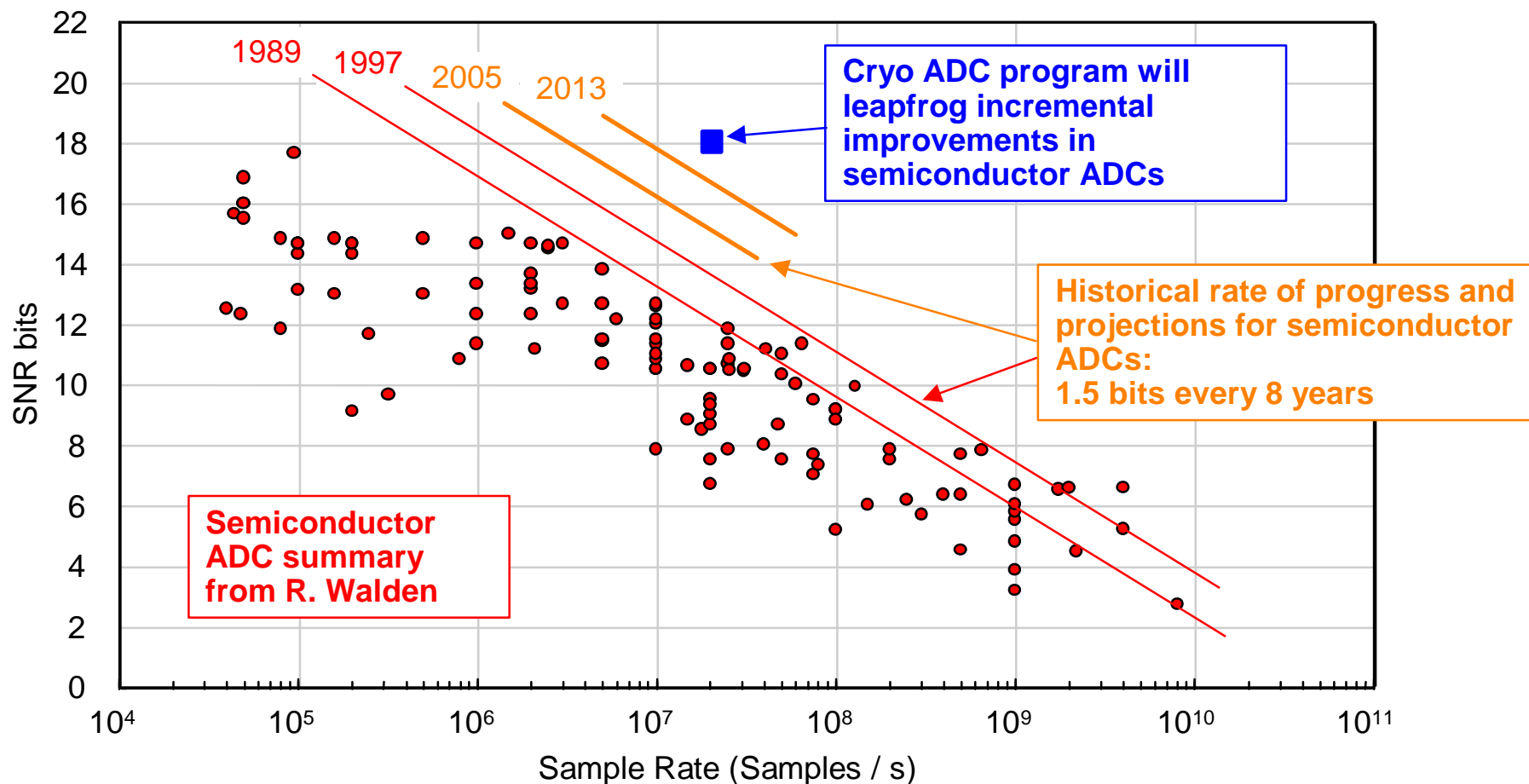
- **Sigma-Delta architectures for linearity**
 - quantization errors remembered and compensated
 - oversampling and feedback to balance the incoming signal
 - standard in the audio recording industry
- **Parallel materials technologies:**
 - LTS for fastest progress in circuit development and availability for shipboard deployment
 - HTS fabrication development for airborne deployment
- **Teaming with NIST on WFG**
 - closely related to JJ-based ac voltage standard
- **Teaming with universities on HTS fabrication development**

Quantized Feedback is the Essential Advantage of an SFQ Design for S- D

- **Sigma-Delta ADCs** use oversampling and feedback for high dynamic range
- **Semiconductor ADCs** balance input with electrons on capacitors. Not repeatable.
- **Superconductor ADCs** balance input with flux quanta. Repeatable. Accurate.

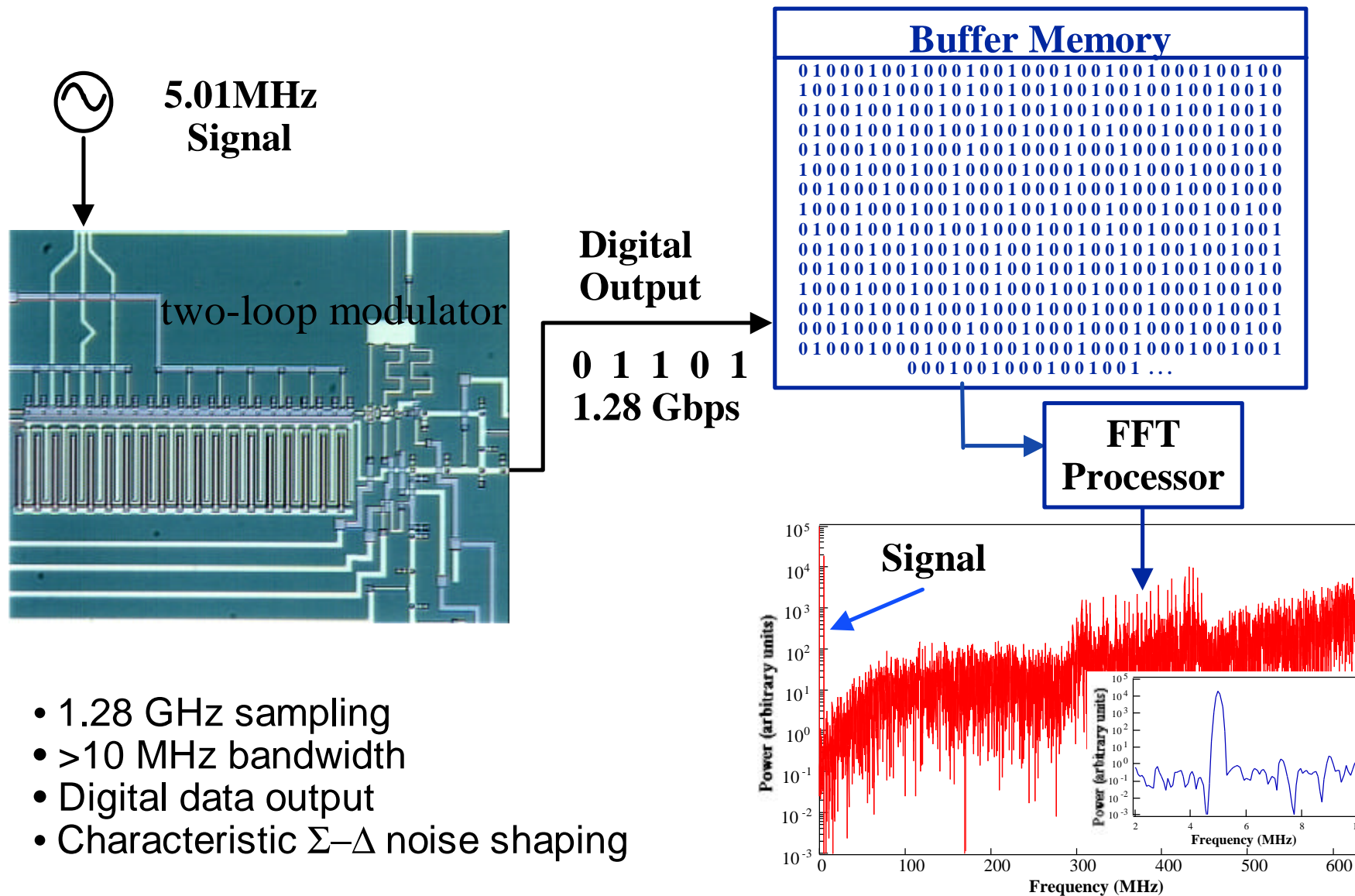


Hybrid ADCs Will Leapfrog the Rate of Progress for Purely Semiconductor ADCs



- Hypres' Approach: All-superconducting, LTS-only architecture, 10^4 junctions
- Northrop Grumman Approach: Super/Semi hybrid, *NORTHROP GRUMMAN* HTS-compatible design, ~350 junctions

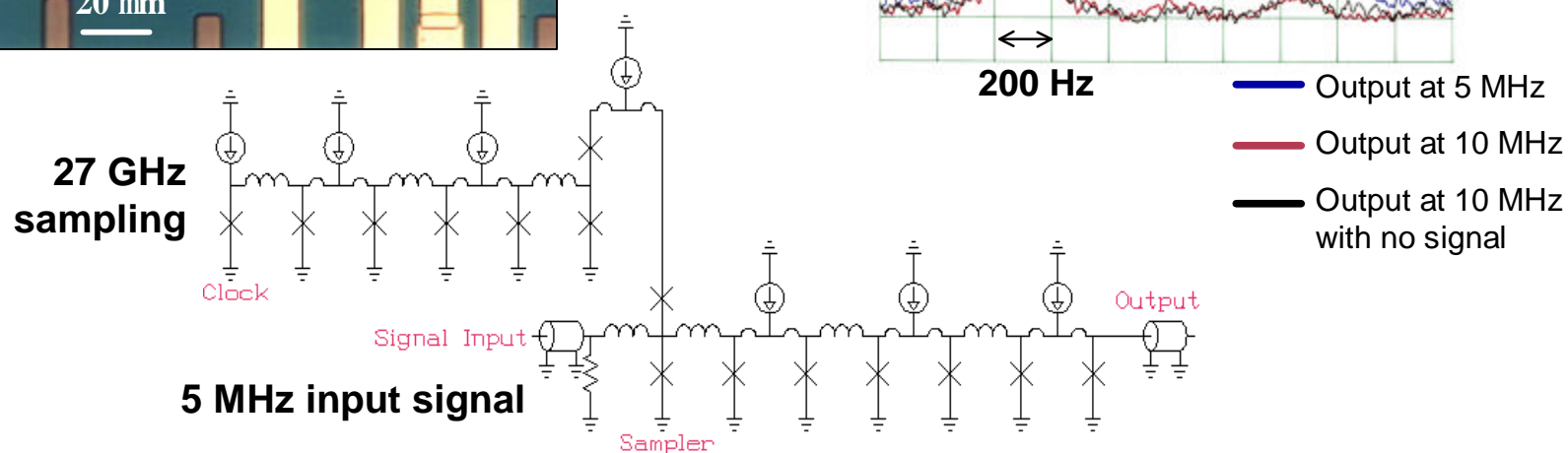
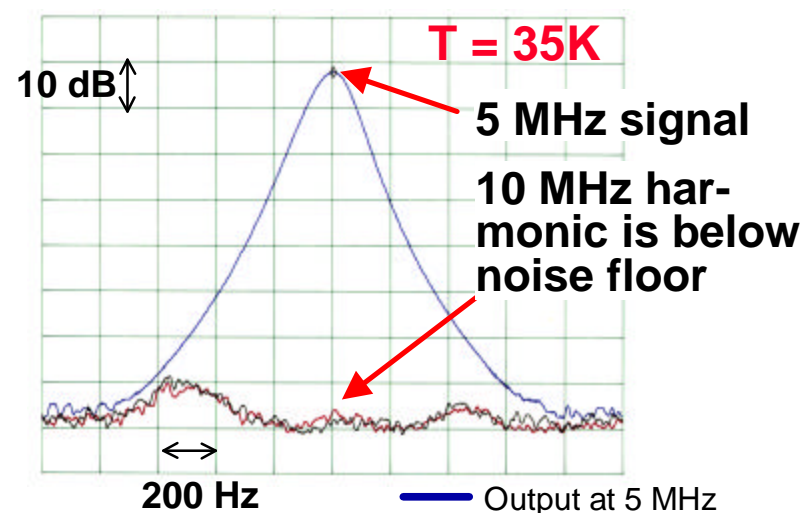
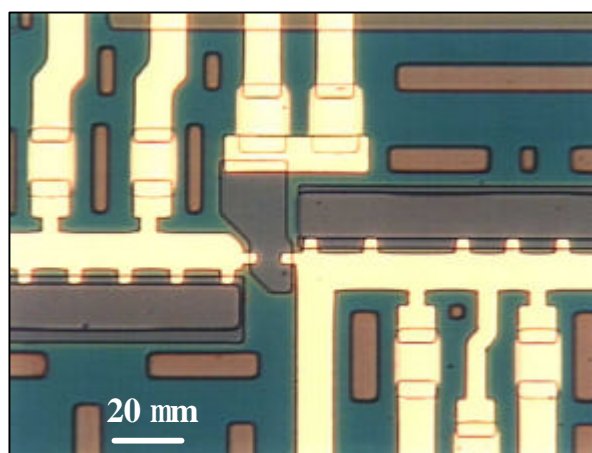
Proof of Principle Demonstrated in JJ ADC Noise Shaping



Linearity Demonstrated for HTS Single-Loop S-D Modulator

HTS circuit demonstrated

- 27 GHz clock
- SFDR > 75 dB
- Third order intermod products -58 dBc
- First HTS demonstration of rf signal conversion



Conclusions

- **Digital HTS electronics are based on circuit speed, low power dissipation, and exploitation of the unique property of flux quantization**
- **Non-uniformity of HTS junction critical currents limits the junction count in circuits to ~100**
- **Most important near-term “digital” HTS subsystems are mixed-signal circuits (ADCs and DACs) requiring just 100s of junctions**
 - **Two ranges of Josephson junction parameters required**
 - **LTS circuits used to develop and validate circuit concepts**
 - **HTS junction integration with groundplanes and passive devices demonstrated in small-scale circuits**